



Radiation Effects in SiGe Devices

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***MURI Review: Vanderbilt University, Nashville, TN
June 13-14, 2008***



Outline

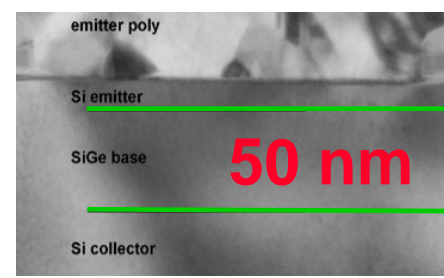
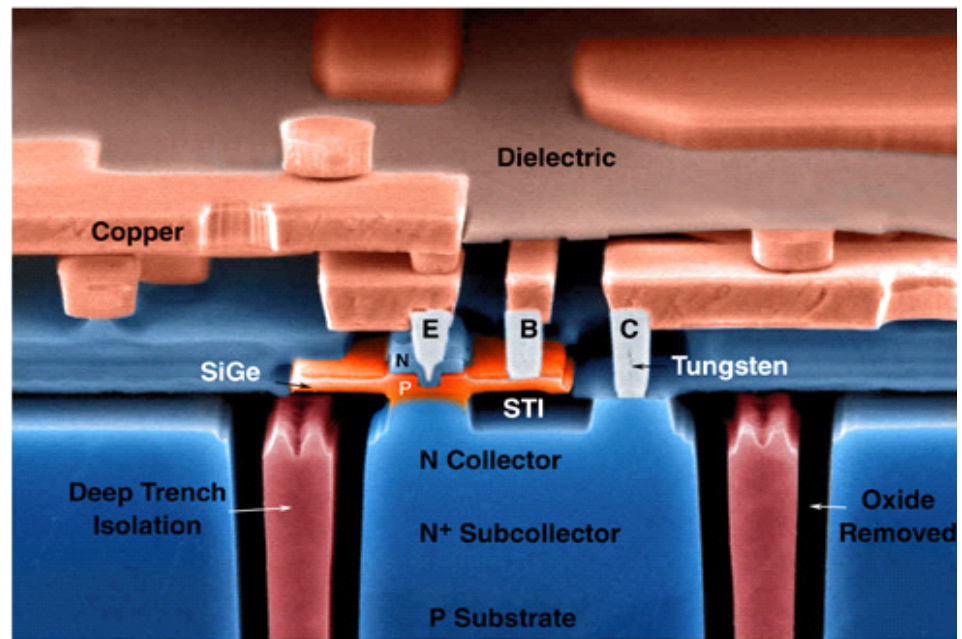
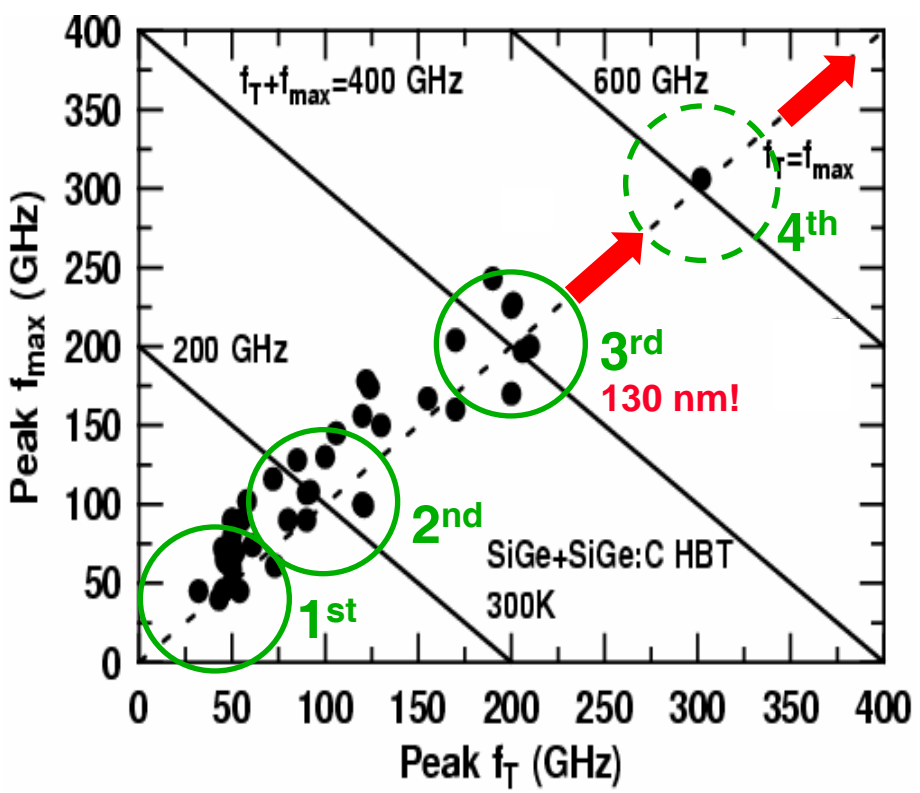


- **Some Updates from the SiGe World**
- **Progress in RHBD for Bulk SiGe HBT Platforms**
 - some new RHBD approaches
- **Radiation Effects in New SiGe Technology Platforms**
 - IBM SiGe 8WL
 - SiGe HBTs on SOI
- **Radiation Effects in Advanced Si/SiGe FETs**
 - SiGe MODFETs (n-channel + p-channel)
 - 65 nm Strained Si RF-CMOS on SOI
- **Progress / Plans**



SiGe Evolution

- SiGe = SiGe HBT + Si CMOS for Highly Integrated Solutions
- **Rapid** Generational Evolution (full SiGe BiCMOS)
- Significant In-roads in High-speed Communications ICs



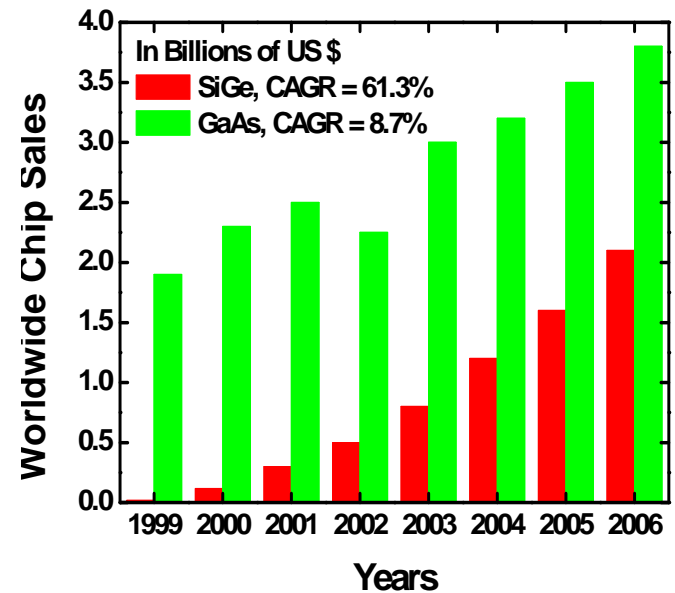
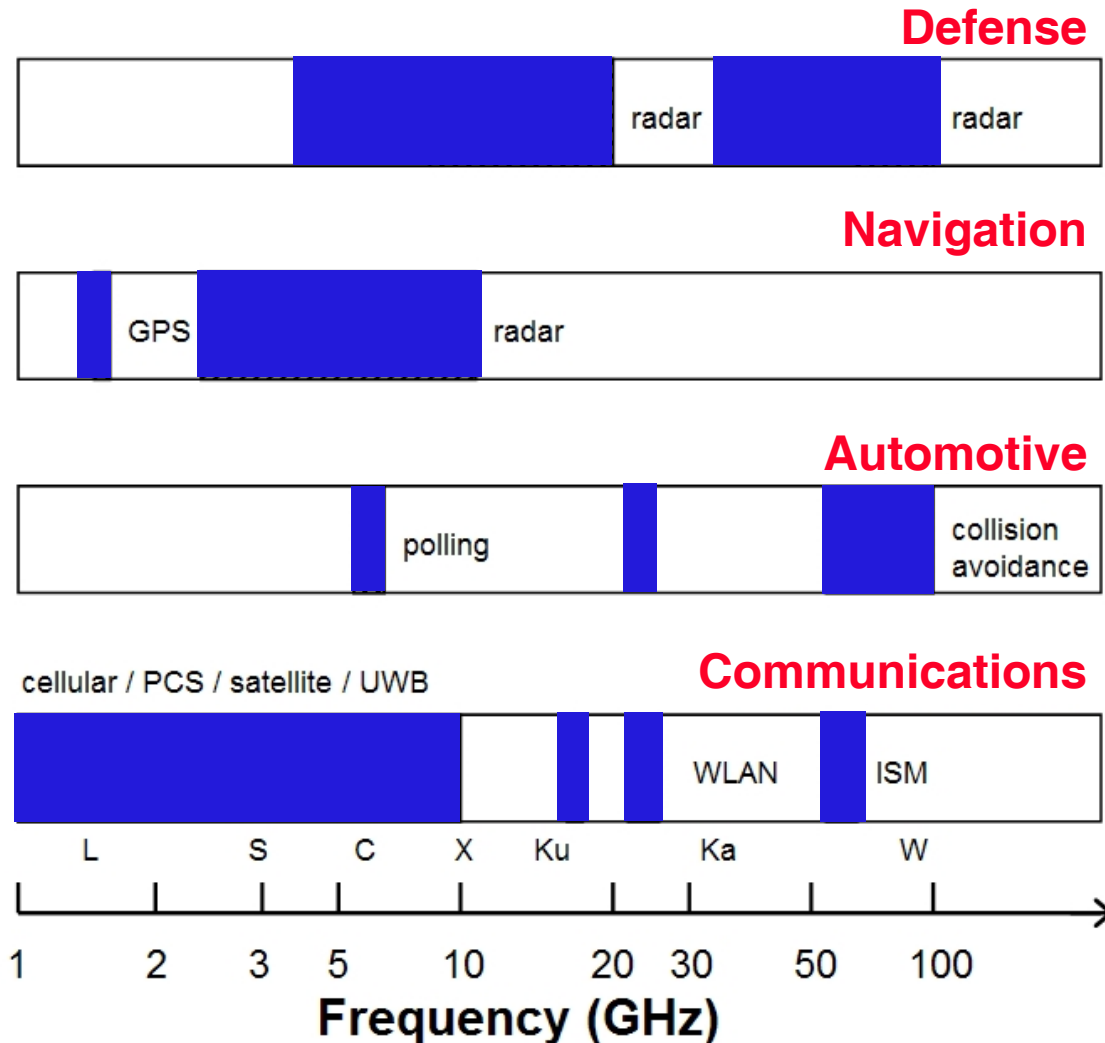
SiGe

SiGe = III-V Speed + Si Manufacturing Win-Win!

SiGe Market



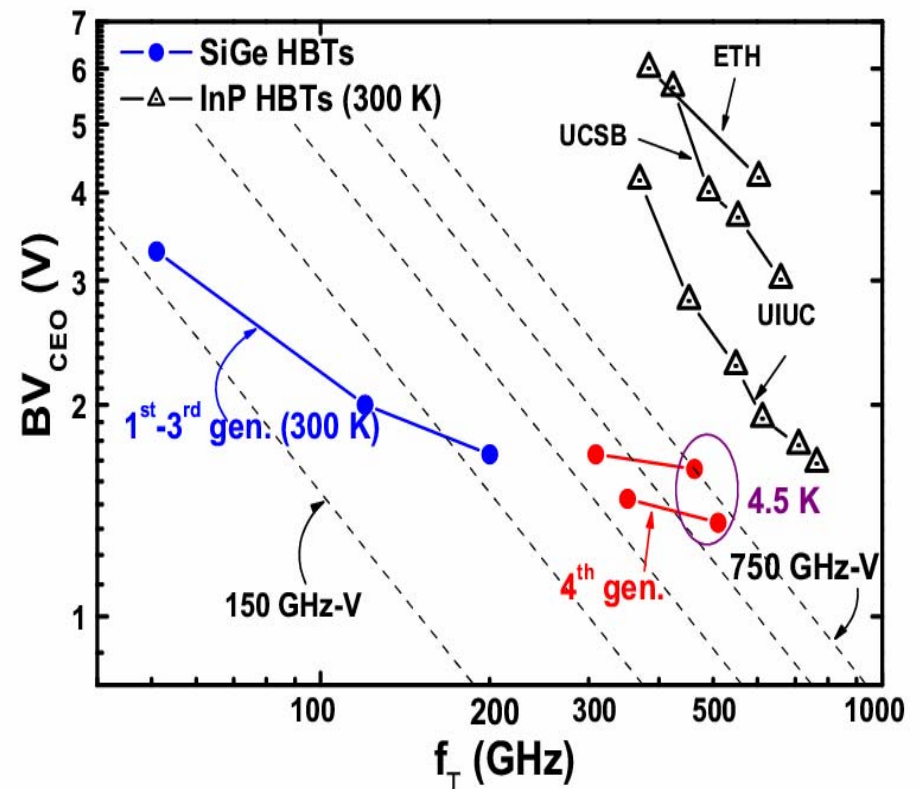
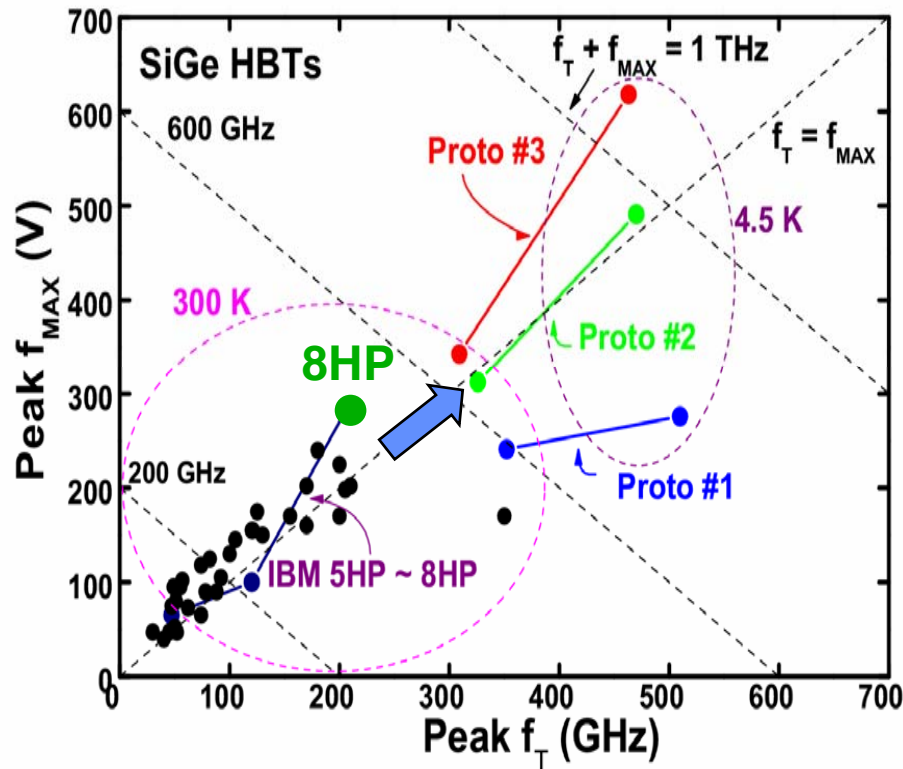
Some Application Bands for SiGe IC's



SiGe Performance Limits



- Half-TeraHertz SiGe HBTs Are Clearly Possible (at modest lith)
- Both f_T and f_{max} above 500 GHz at Cryo-T ($T = \text{scaling knob}$)
- Goal: Useful BV @ 500 GHz ($BV_{CEO} > 1.5 \text{ V} + BV_{CBO} > 5.5 \text{ V}$)



200-500 GHz @ 130 nm Node!



New Opportunities

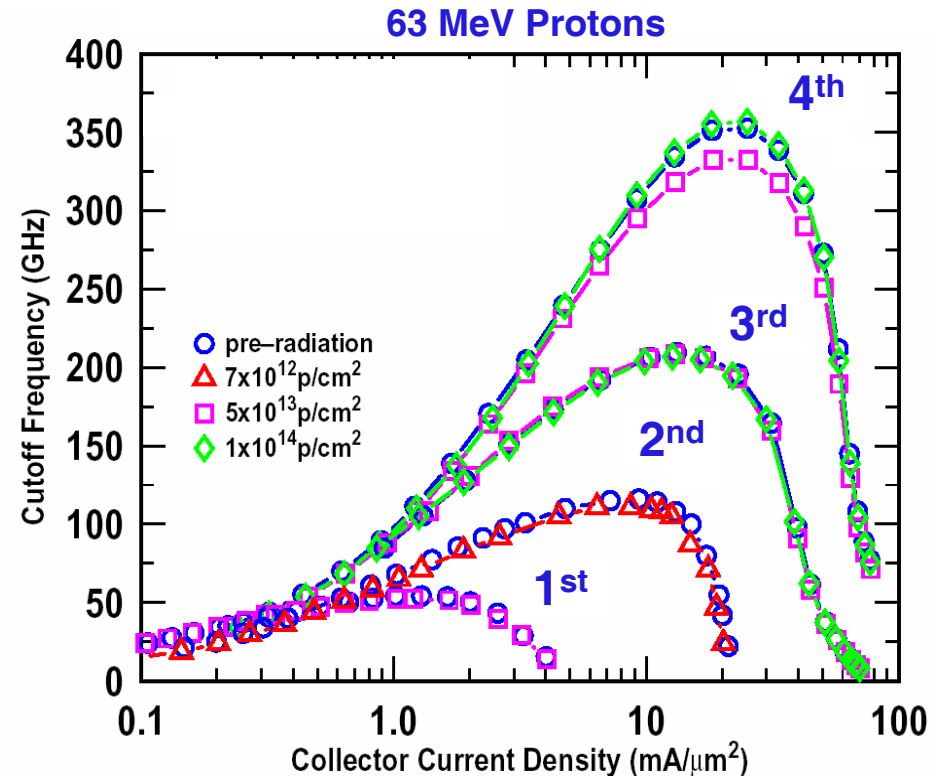
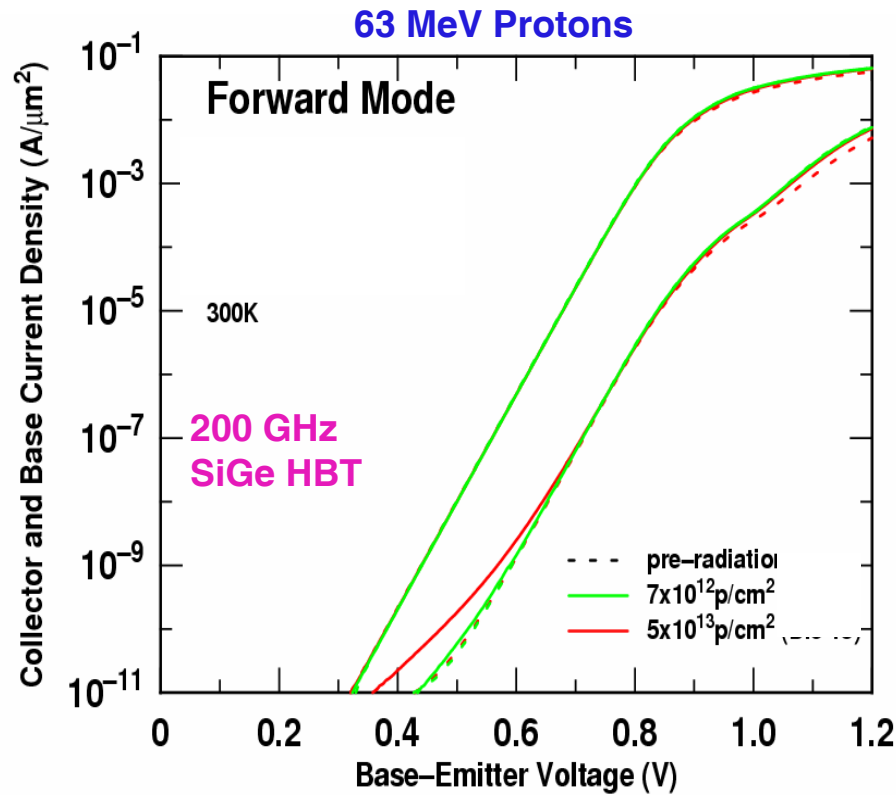
- **SiGe for Radar Systems**
 - DoD phased arrays (2-10 GHz and up) + automotive (24, 77 GHz)
- **SiGe for Millimeter-wave Communications / THz Imaging**
 - Gb/s wireless (60, 94 GHz) / imaging systems (100-300 GHz)
- **SiGe for Analog Applications**
 - data conversion (ADC limits) + the emerging role of C-SiGe (nnp + pnp)
- **SiGe for Extreme Environment Electronics**
 - extreme temperatures (4K to 300C) + radiation (e.g., space systems)
 - explore performance limits of SiGe (goal: 1 THz aggregate $f_T + f_{max}$)
- **SiGe for Enhanced Dynamic Range Systems**
 - improved understanding of linearity / extreme wideband transceivers

All Are Highly DoD Relevant!

Total-Dose Response



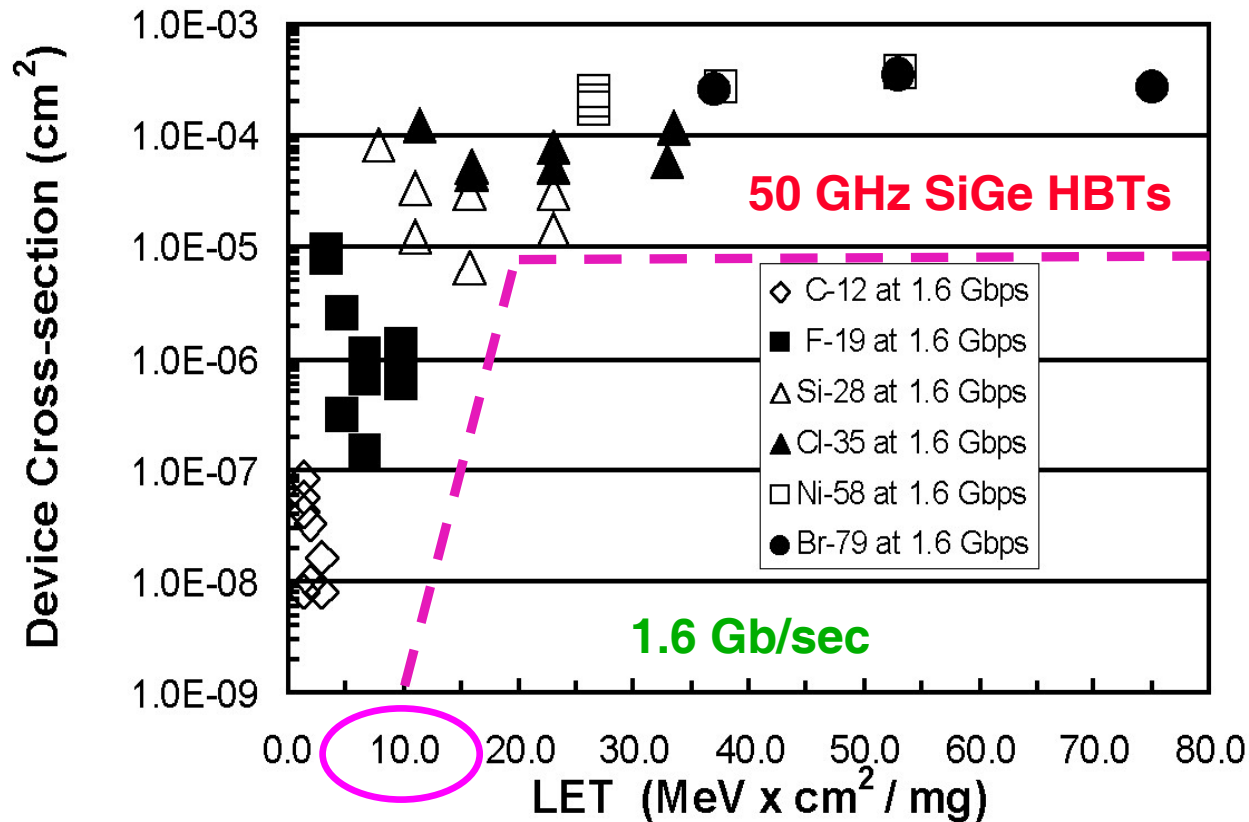
- **Multi-Mrad Total Dose Hardness (with no intentional hardening!)**
 - ionization + displacement damage very minimal; no ELDRS either!
- **Radiation Hardness Due to Epitaxial Base Structure (not Ge)**
 - thin emitter-base spacer + heavily doped extrinsic base + very thin base



Single Event Effects



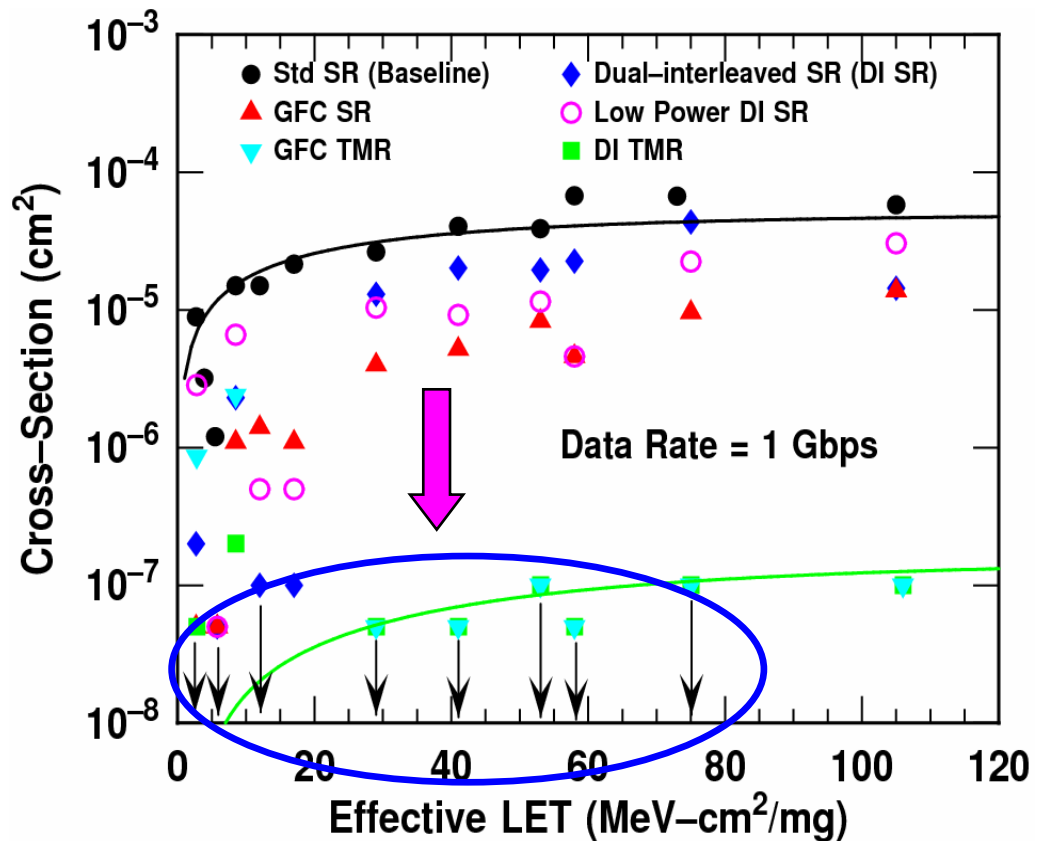
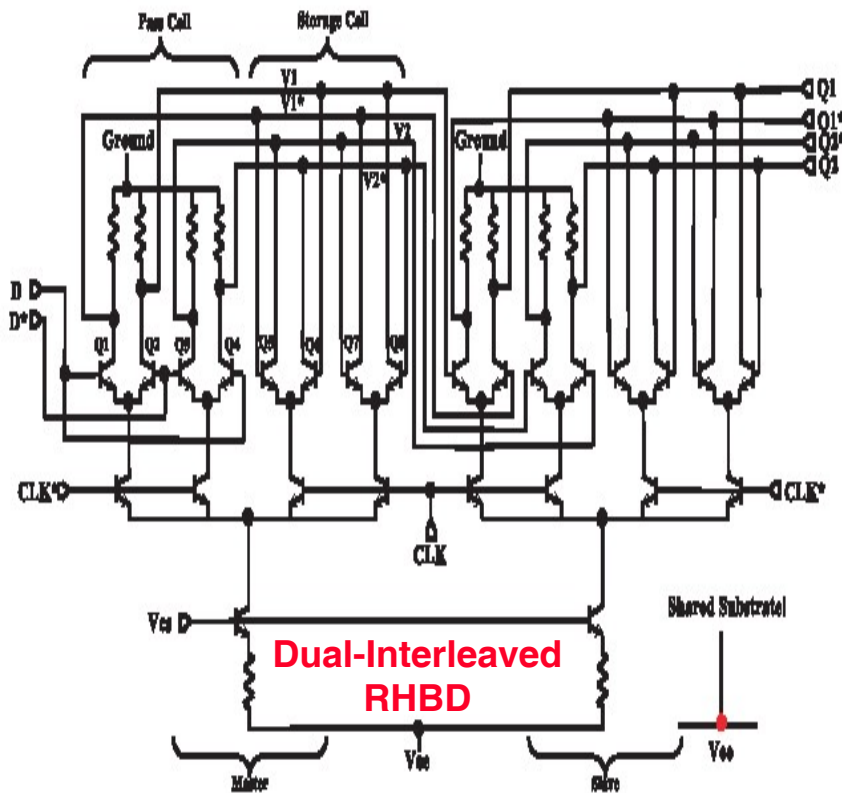
- **Observed SEU Sensitivity in SiGe HBT Shift Registers**
 - low LET threshold + high saturated cross-section





SEU RHBD in SiGe

- Reduce Tx-Tx Feedback Coupling Internal to the Latch
- Circuit Architecture Changes + Transistor Layout Changes

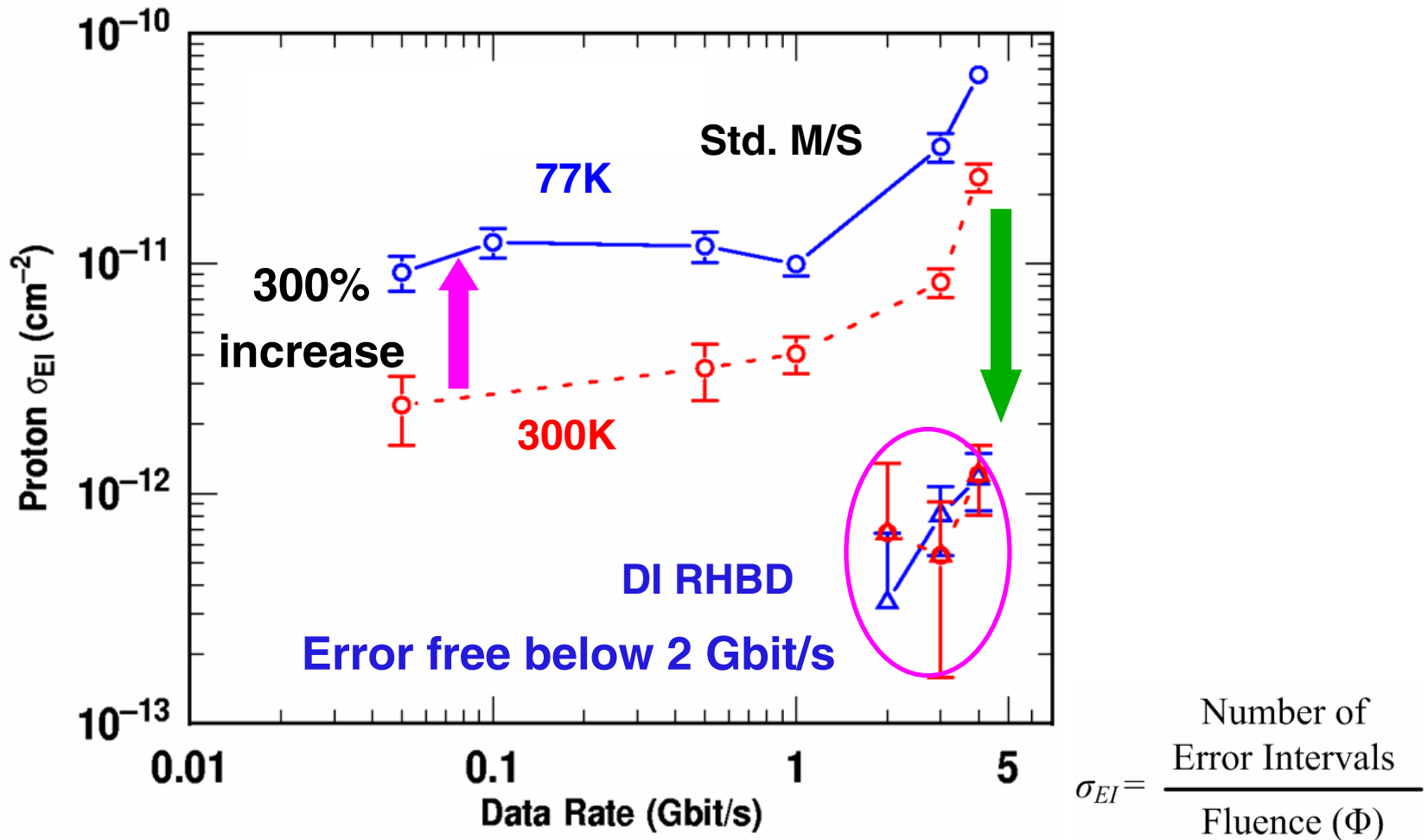


Q: Can We Eliminate TMR?

Proton Cross-Section



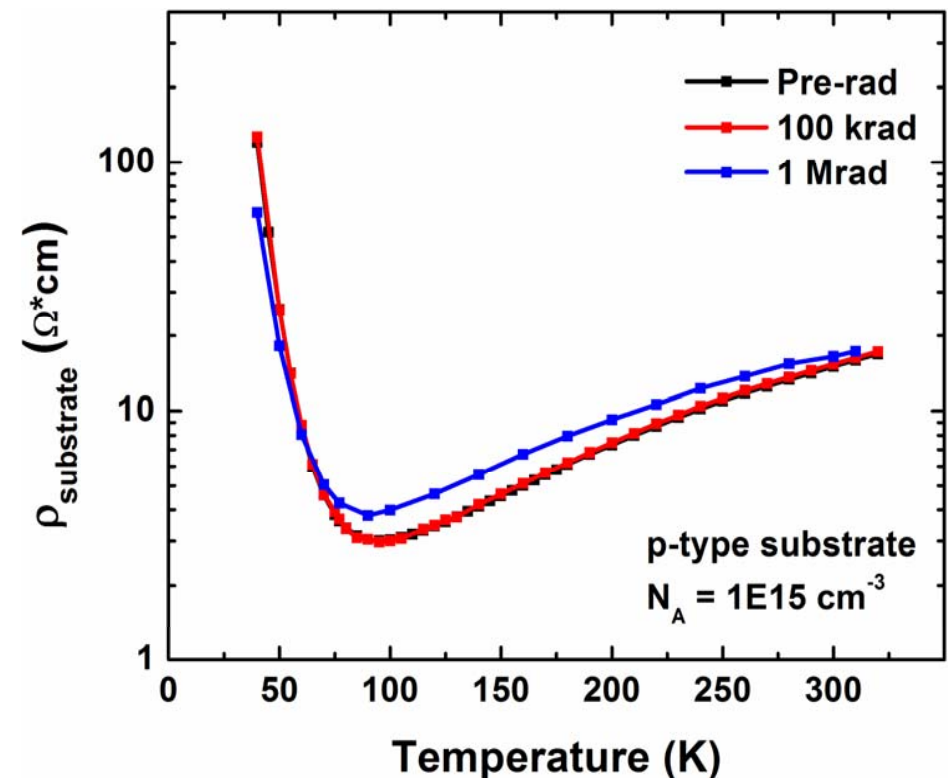
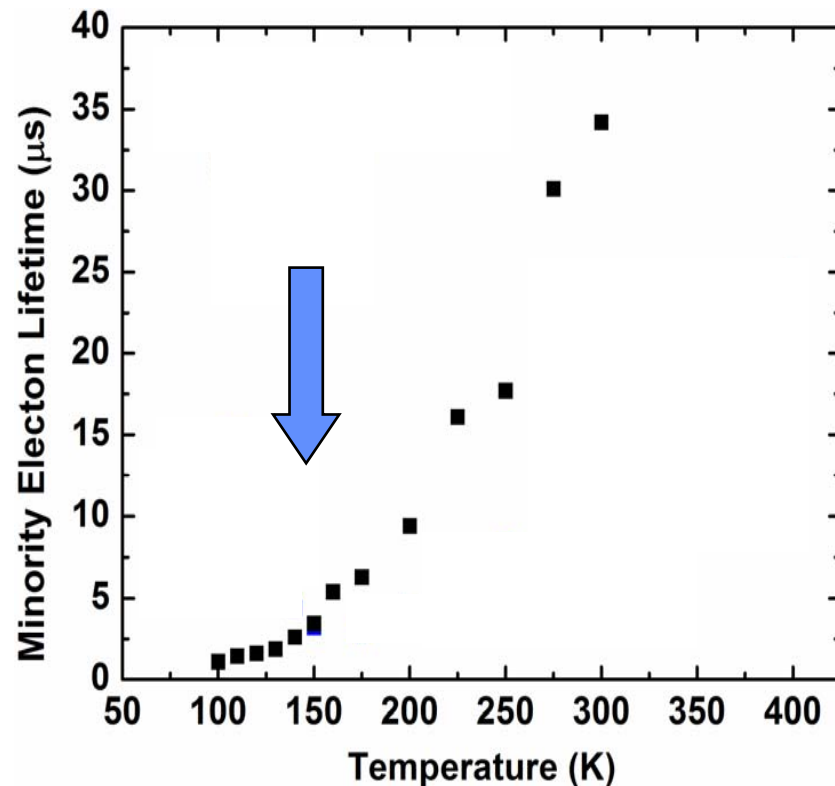
- Proton σ_{EI} is 5 Orders of Magnitude Less Than Heavy Ion σ_{EI}
- 3X **Increase** in Proton Cross-section at **77K** for Std. M/S ... **BUT**
- DI RHBD is Error-free < 2 Gbit/s and Insensitive to Temperature



Transport Parameters



- Bulk Minority Carrier Lifetime in Substrate as $f(T)$
- Substrate Resistivity (mobility) as $f(T)$ – **Key for SEU**



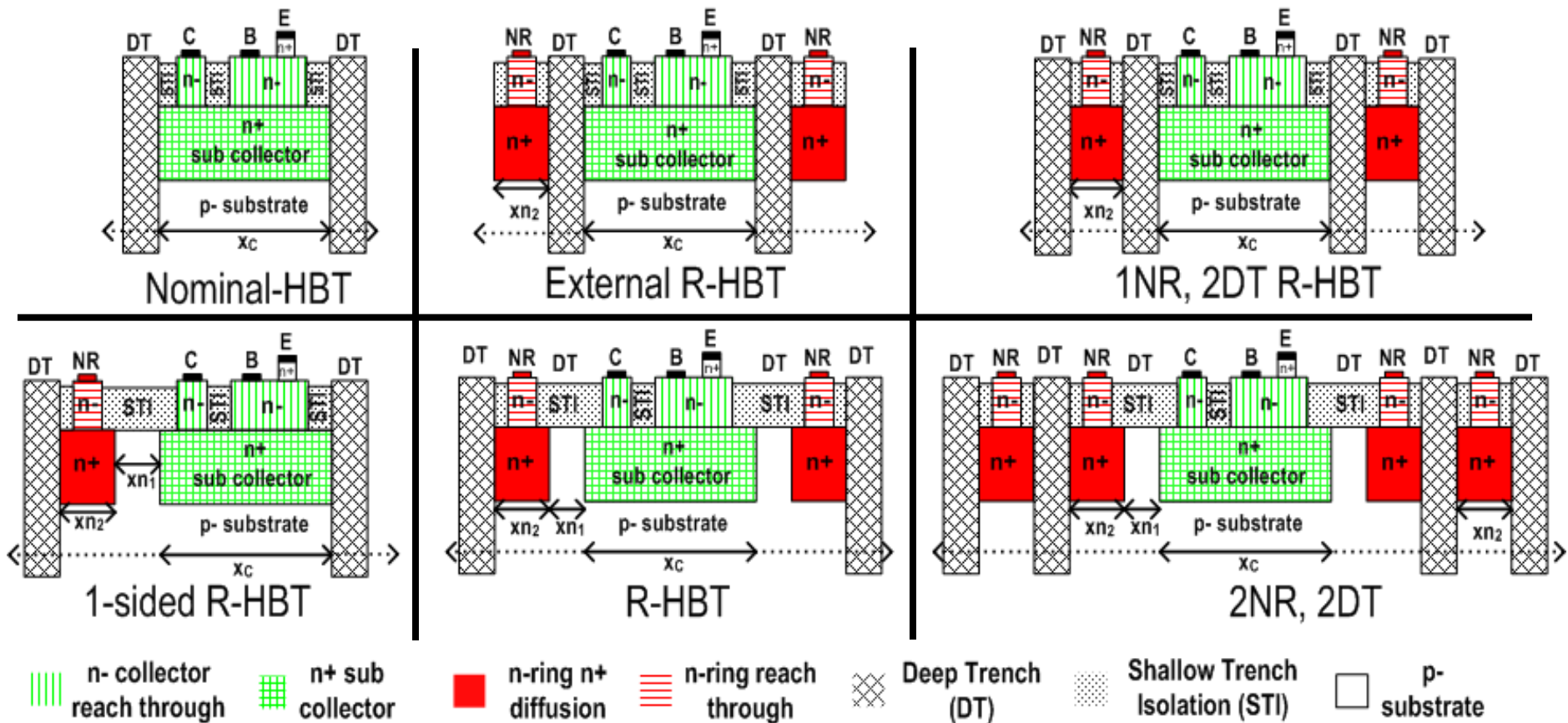
Robust Measurements are NON-TRIVIAL!

Layout-Based RHBD



- **Alternate Reverse-biased pn Junction** (*Sx to N-ring*)

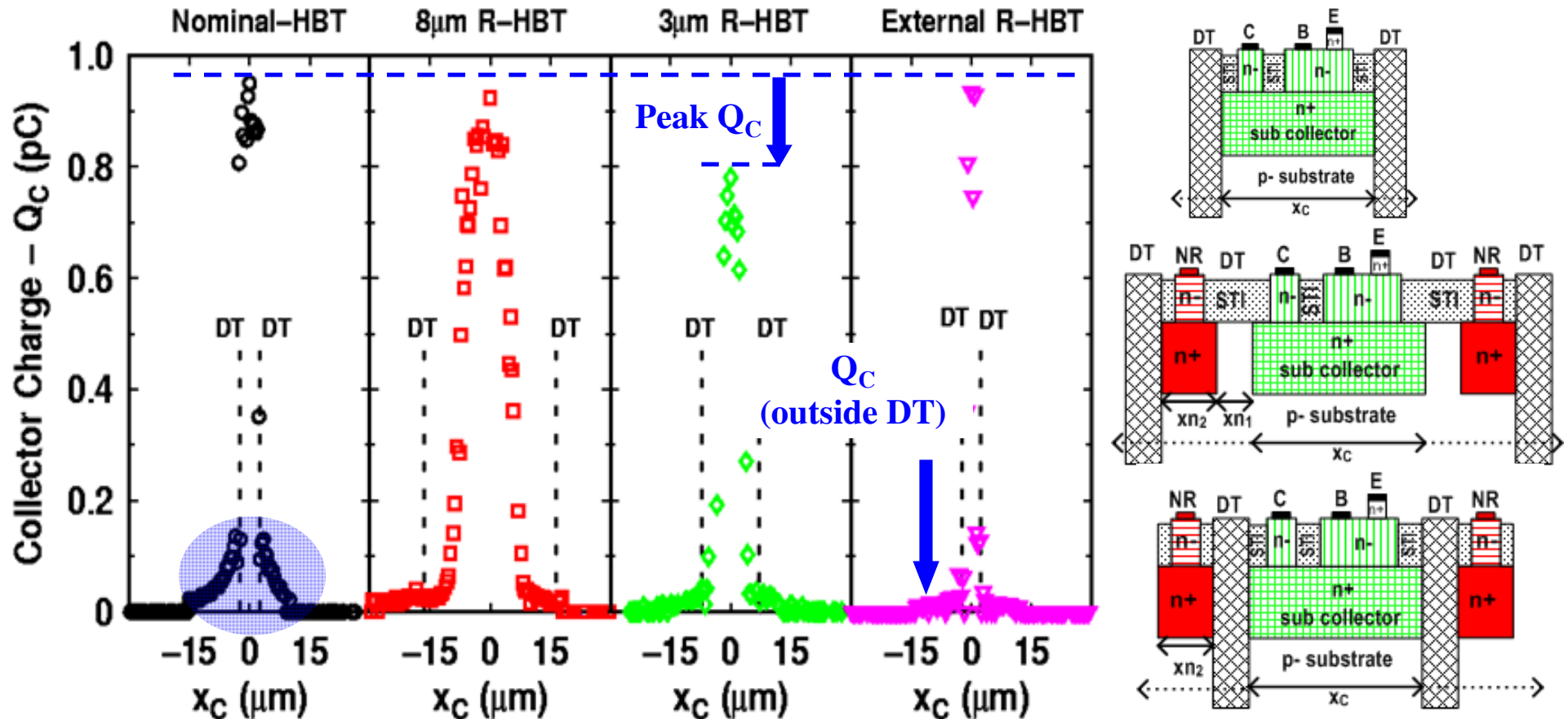
- identical doping profile to device sub-collector
- internal and/or external DT placement possible



Microbeam Testing



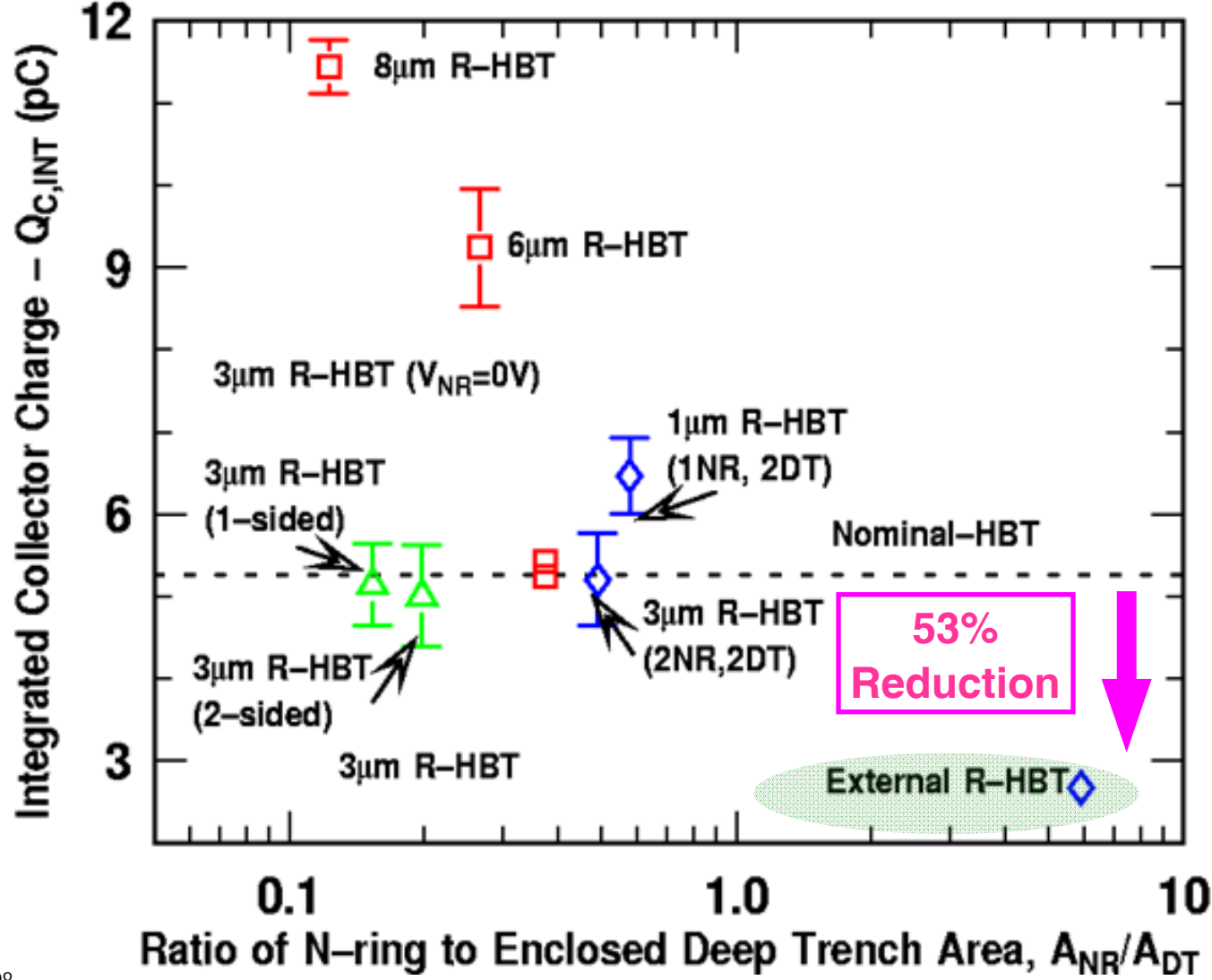
- **5-probe IBICC Measurement (Sandia National Lab)**
 - 36 MeV O_2 ions, LET= 7 MeV-cm²/mg, 25 μ m Si range
 - 100 μ m² scan, $V_C=V_B=V_E=0$ V, $V_{SX} = -4$ V, $V_{NR} = 0 - 4$ V



RHBD Bottom-Line



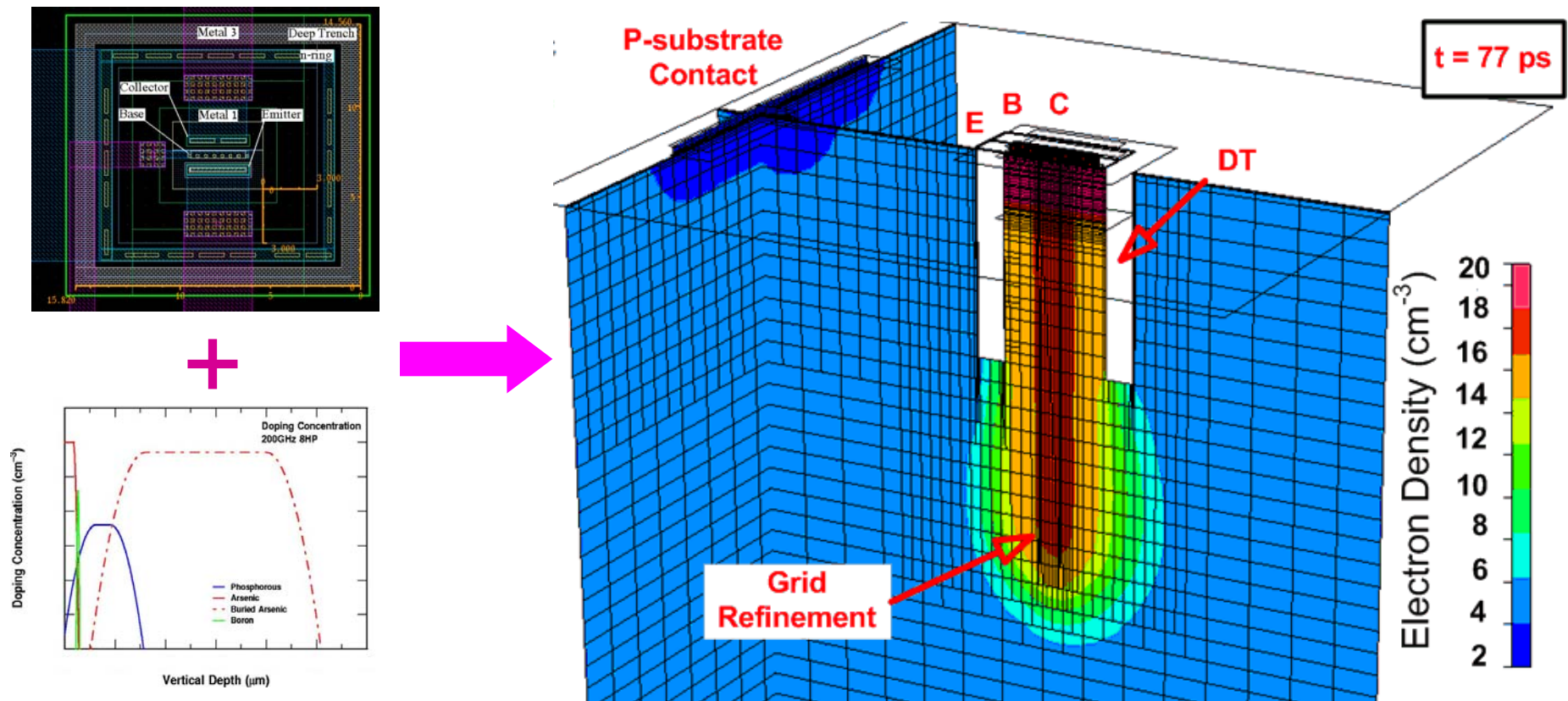
- $Q_{C,INT}$ Decreases with Increasing A_{NR}/A_{DT}



TCAD SEU Simulations



- **NanoTCAD 3-D Ion Strike Simulations (CFDRC SBIR)**
 - Cadence layout + SIMS profile \rightarrow **3-D solid geometry**
 - encased in wrapping layer (absorbing boundary $\tau_w=50$ ns)
 - SRH + Auger; doping, E-field, scattering dependent models

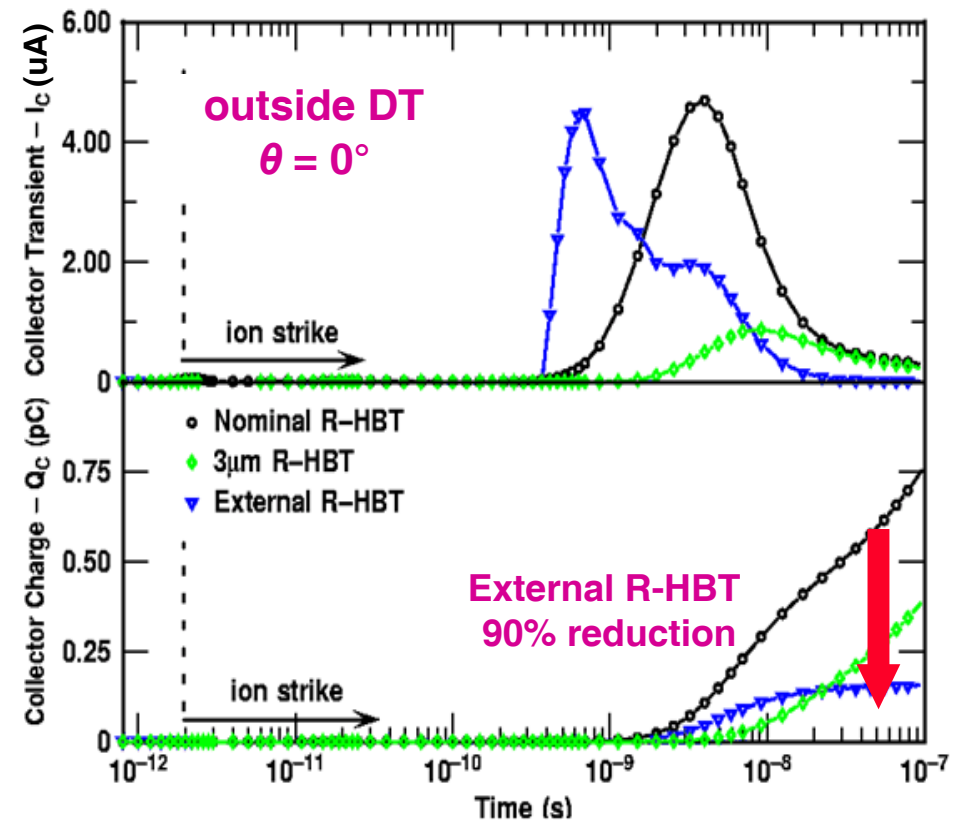
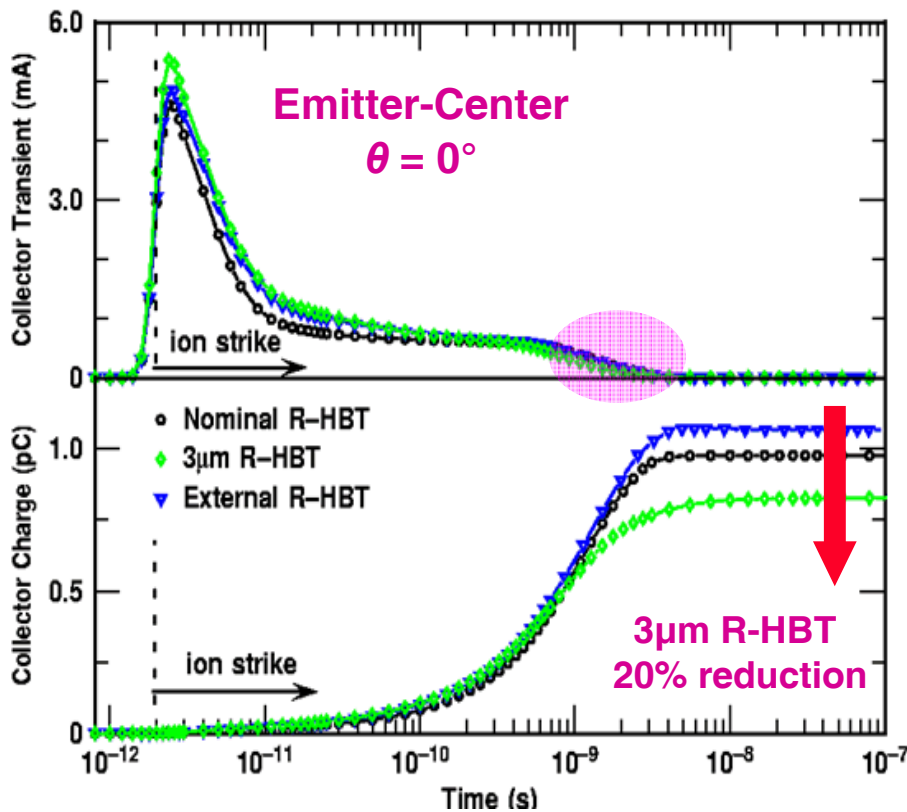


SE Transients



• RHBD (E-center vs. outside DT strikes)

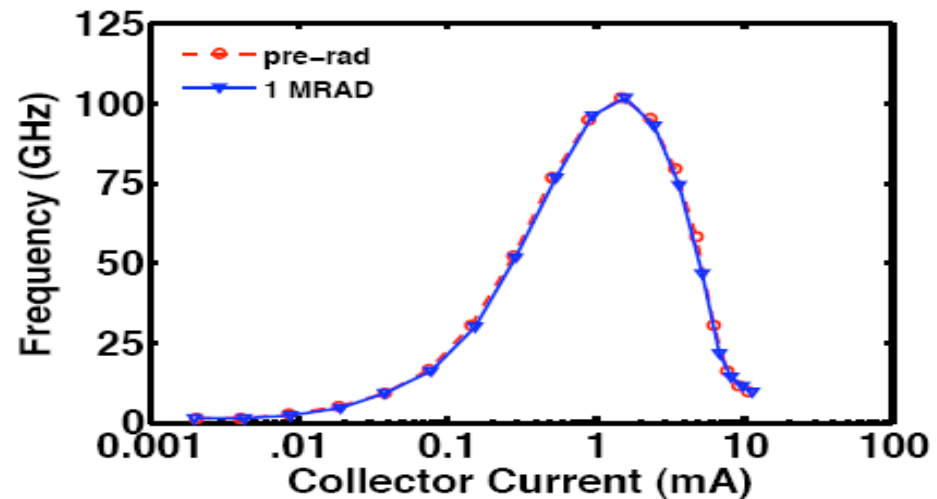
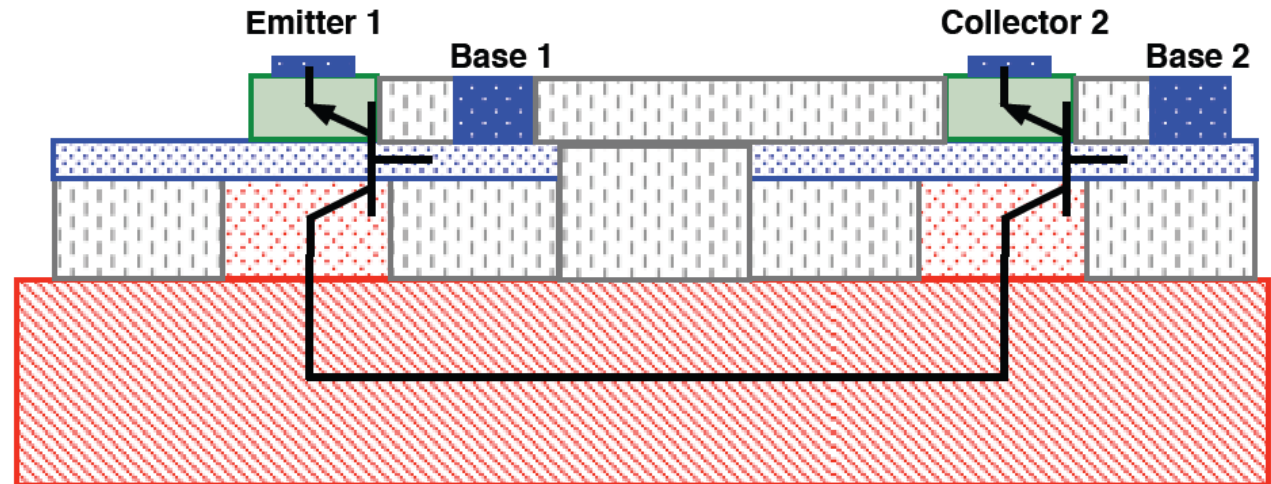
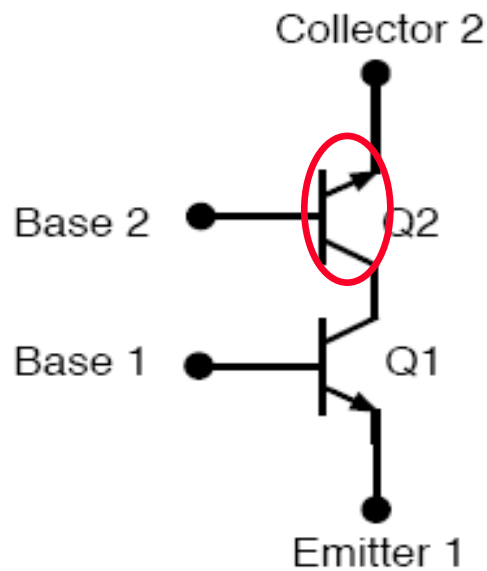
- n-ring does not affect prompt collection (drift dominated)
- 3 μm R-HBT E-center strike \rightarrow 20% reduced Q_C
- external R-HBT outside DT strike \rightarrow 90% reduced Q_C !



Inverse-Cascode RHBD



- Cascode Structure with Inverse Mode Common-Base Device
- Compact Layout + Excellent Performance! Q: SEU Leverage?

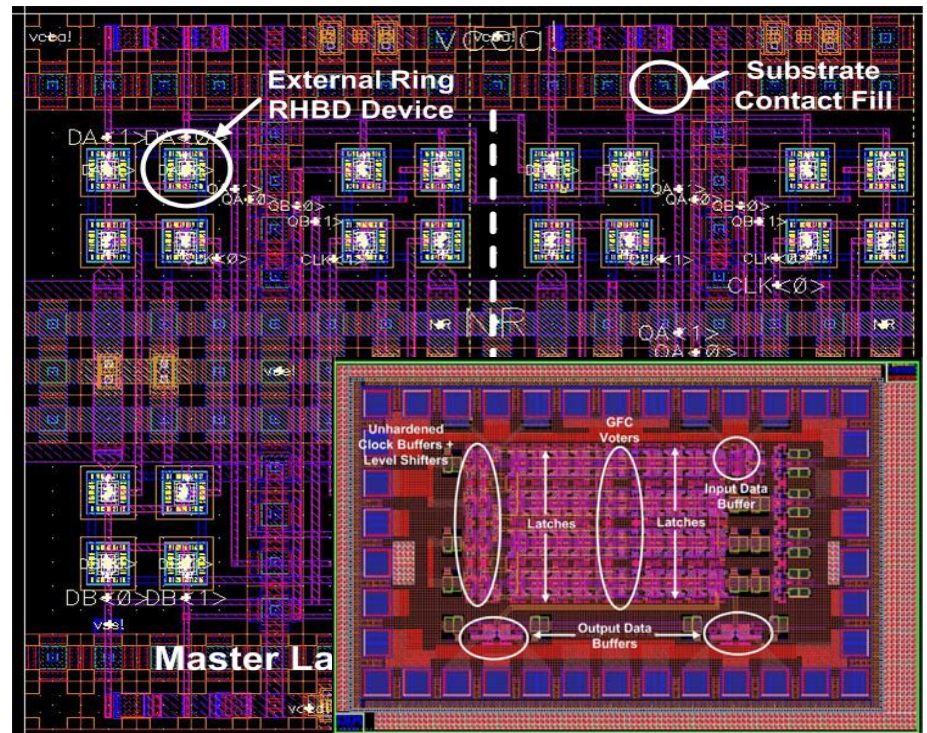
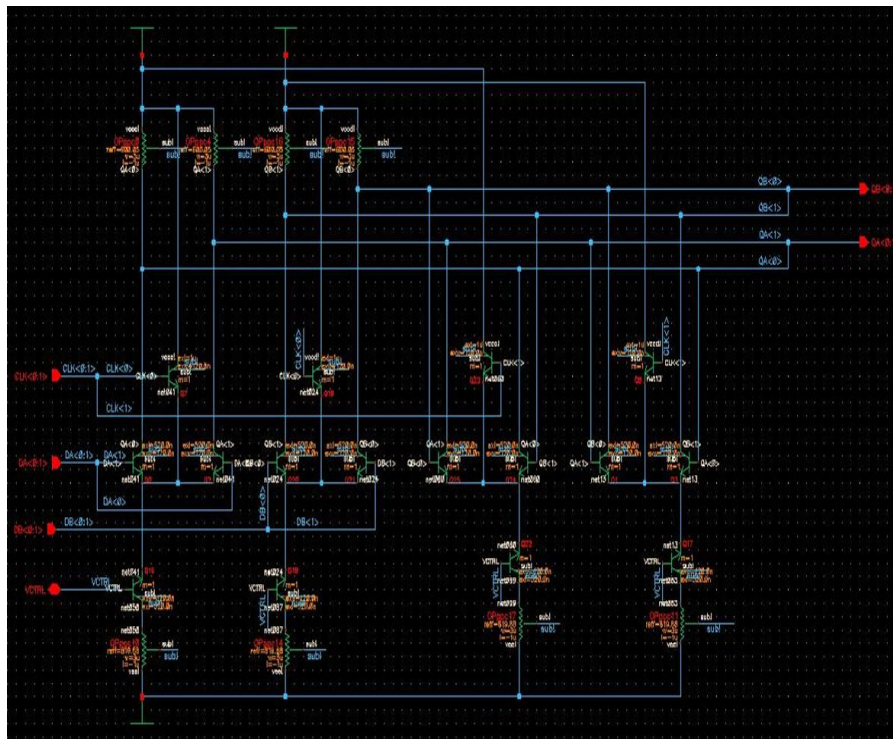


New Circuit-level RHBD



- “Triple Tail Cell Latch”

- clock transistors emitter-coupled to differential pair
- inverse voltage controlled current source + dual interleaved
- 8HP 16-bit SR with GFC + device hardened buffers (in fab)





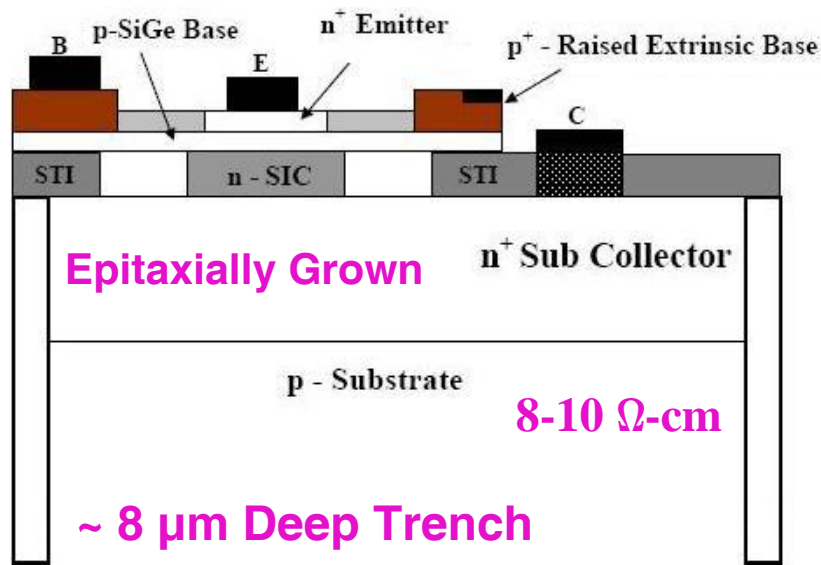
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IBM 8WL SiGe BiCMOS

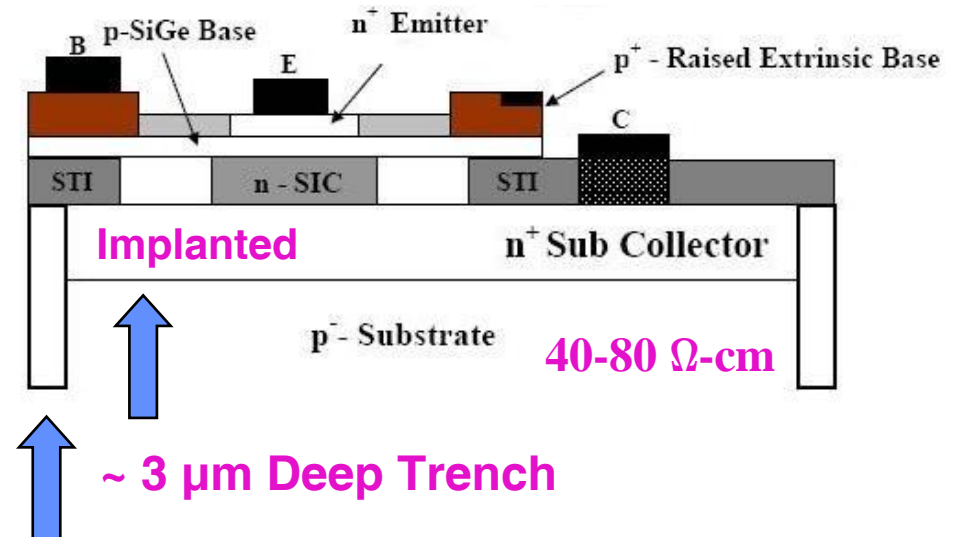


- **Cost-Performance Platform Incorporating 130 nm SiGe HBTs**
 - implanted subcollector (**much shallower subcollector-substrate jx**)
 - “shallow” deep trench isolation $\sim 3 \mu\text{m}$ (**vs. $8 \mu\text{m}$ for 8HP**)
 - lightly doped substrate $\sim 40\text{-}80 \Omega\text{-cm}$ (**vs. $8\text{-}10 \Omega\text{-cm}$ for 8HP**)
 - 100 / 200 GHz peak f_T / f_{max} (**vs. 200 / 285 GHz for 8HP**)

8HP SiGe HBT



8WL SiGe HBT

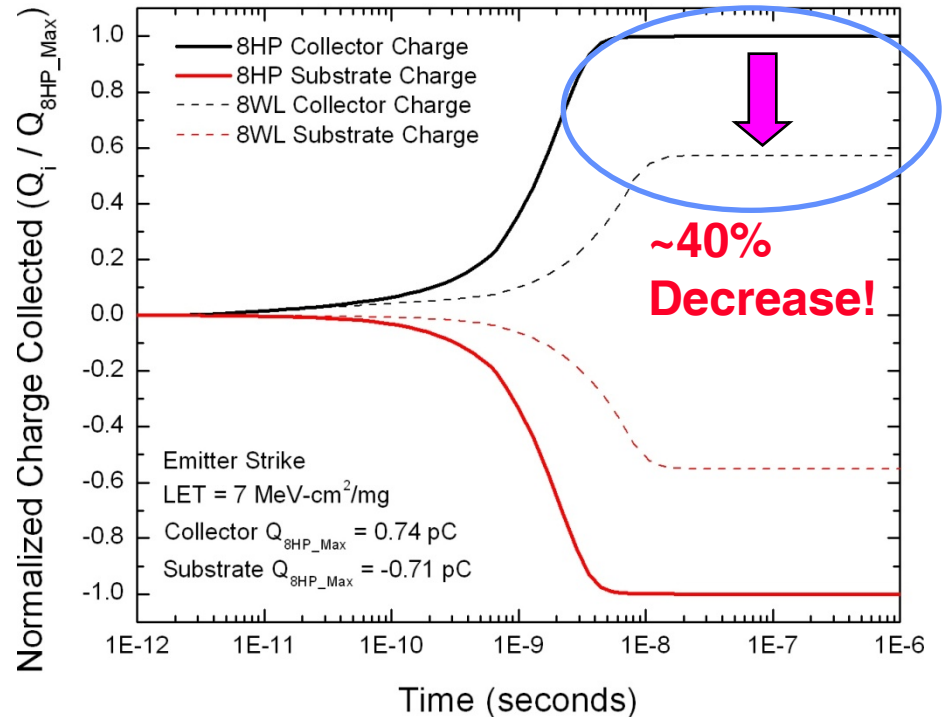
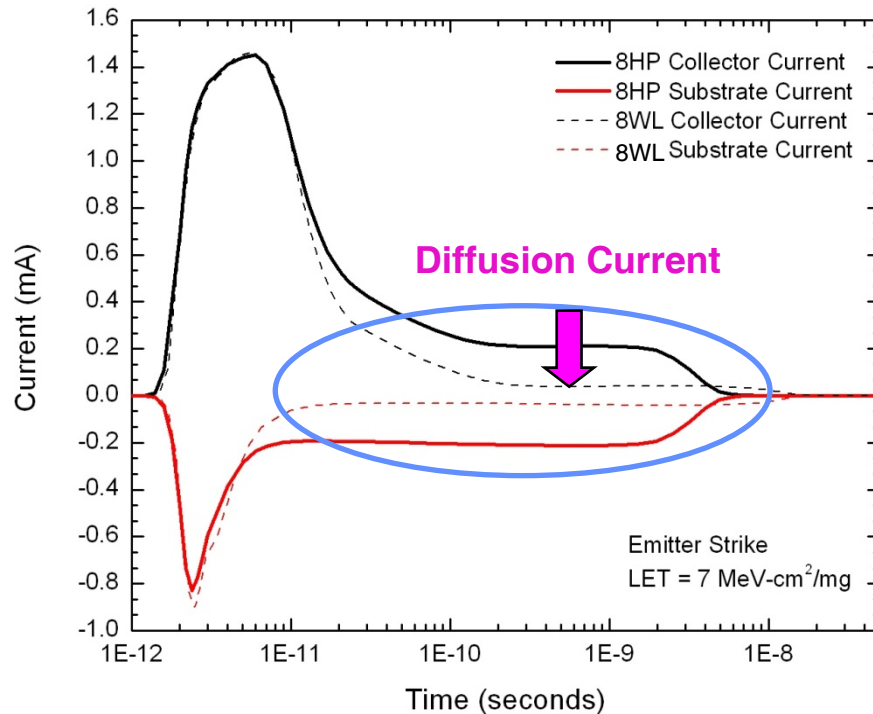


Q: Impact on Charge Collection / TID Response?



8HP vs. 8WL SEU

- Drift-Dominated Charge Collection Similar for 8HP and 8WL
 - ... BUT ...
 - Diffusion-Dominated Charge Collection Suppressed in 8WL
- Q: Less Charge Confinement Inside DT?**

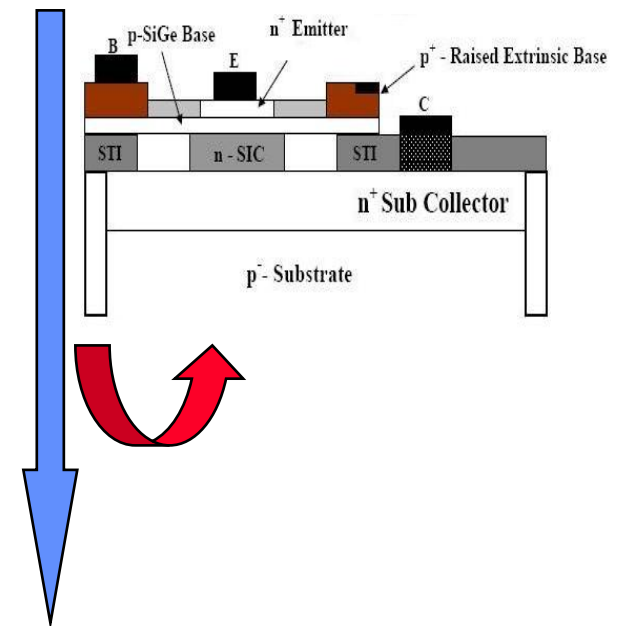
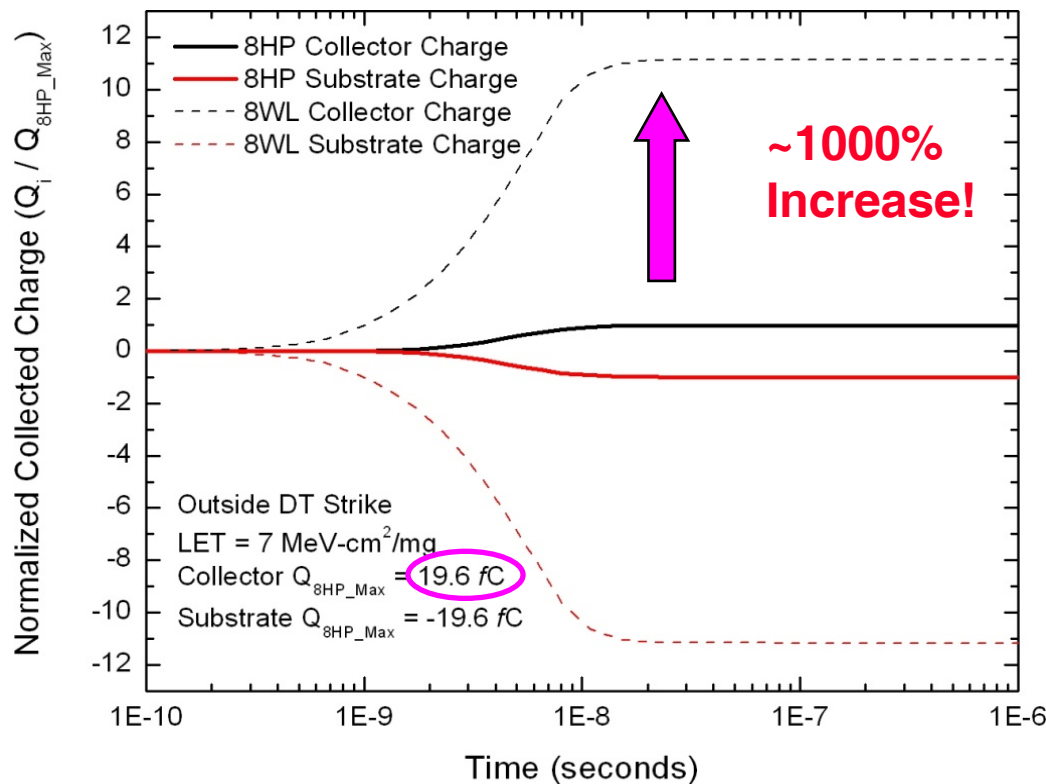


Emitter-Center Ion Strike



8HP vs. 8WL SEU

- **Shallower Deep Trench** → **less isolation for outside DT hit**
 - more carrier diffusion (**Q: higher substrate mobility / lifetime?**)
 - BUT ... Small Absolute Change** → **Net Win for Charge Collection**

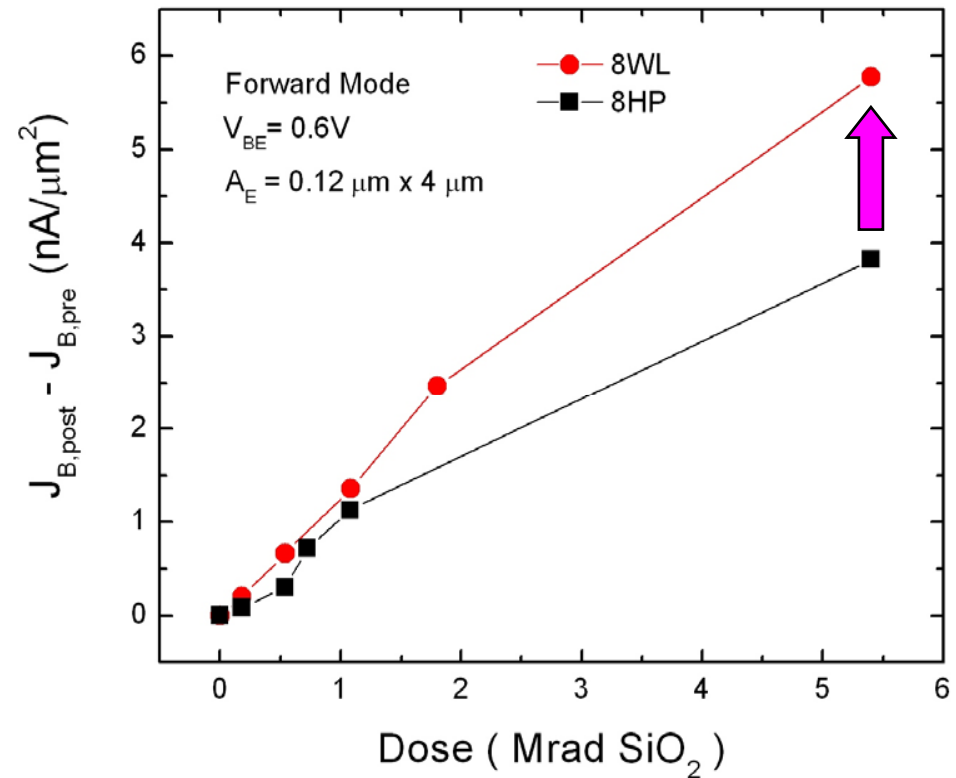
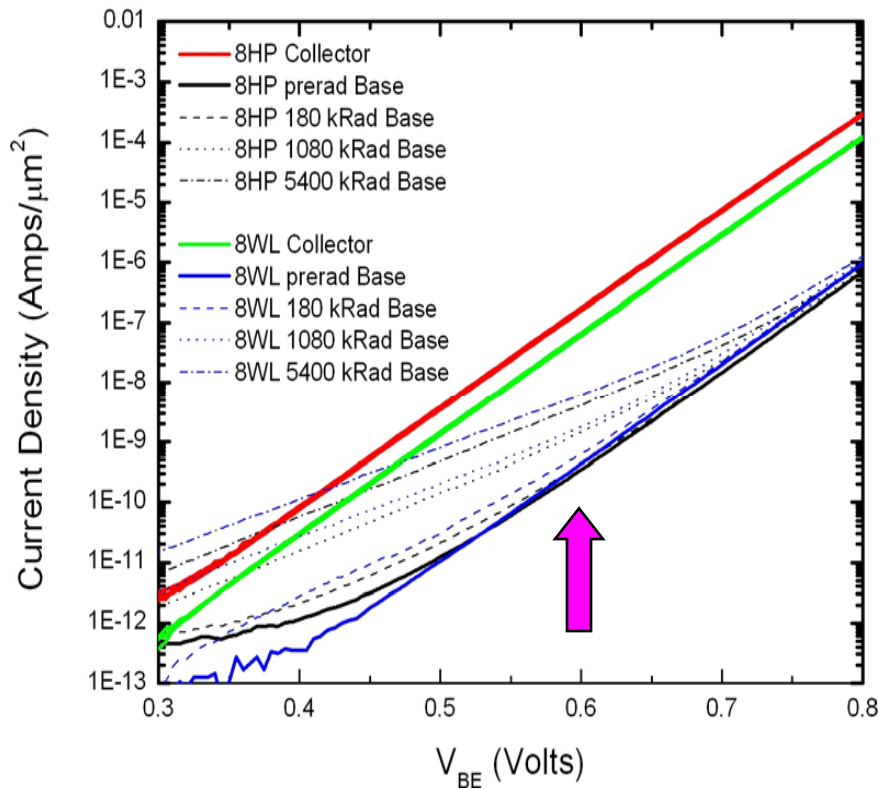


Outside Deep-Trench Ion Strike



8WL TID Response

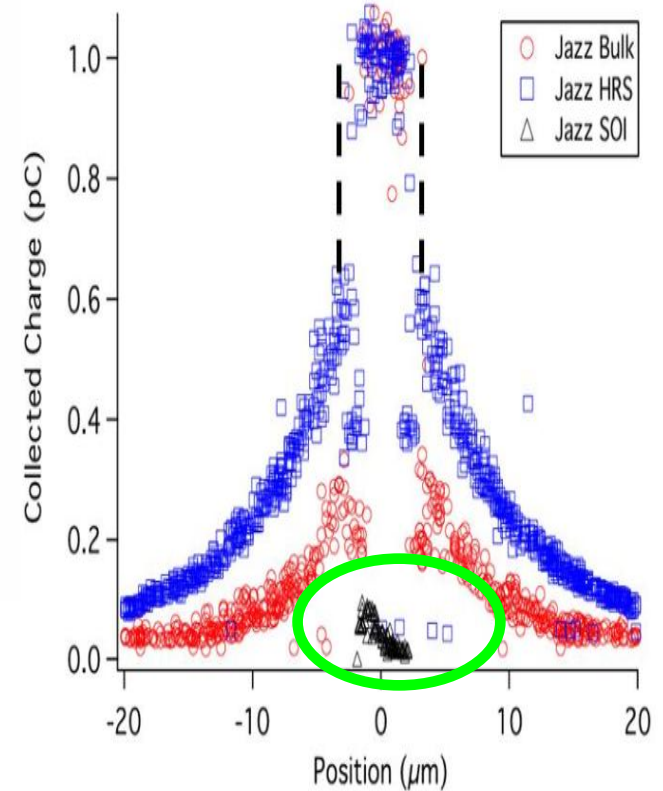
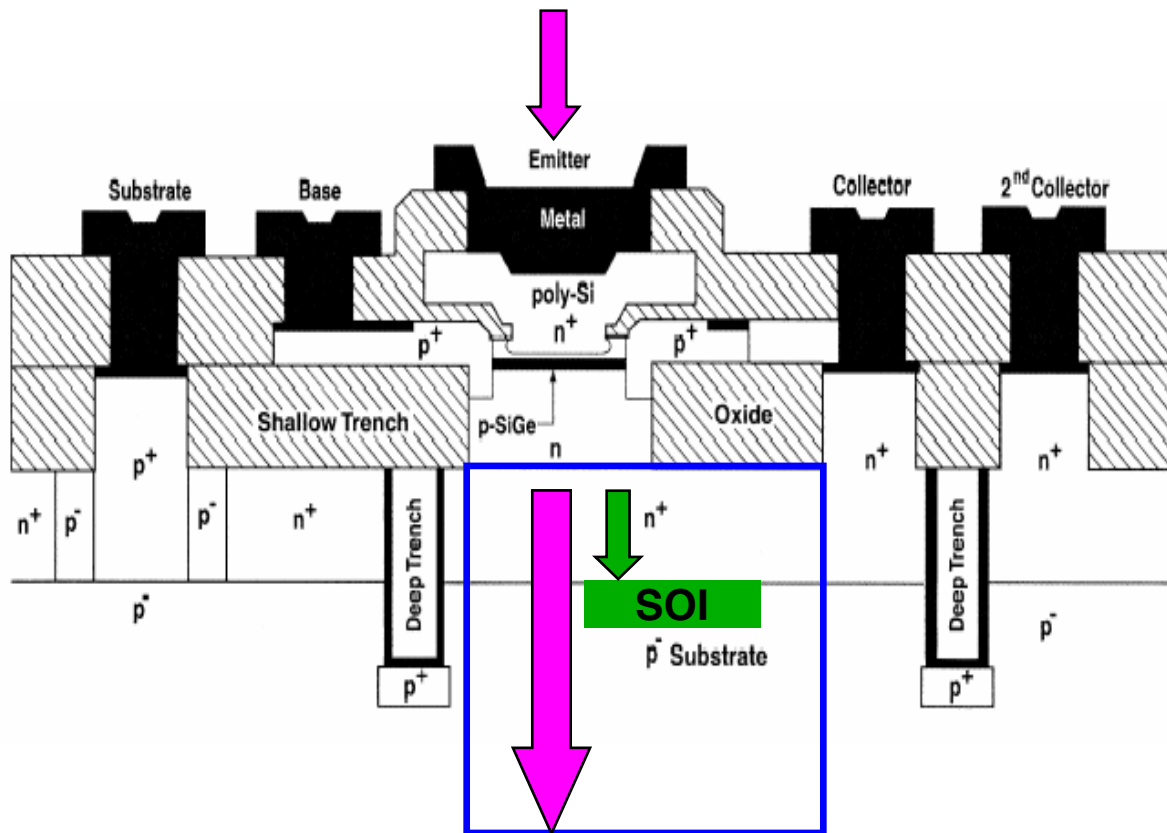
- 8WL & 8HP HBTs Irradiated up to 5.4 Mrad with 10 keV X-rays
- 8WL Has Enhanced Degradation Compared to 8HP
 - Q: impact of different doping / vertical profile?
 - Q: differences in EB / STI oxide processing?



The Path to SiGe on SOI



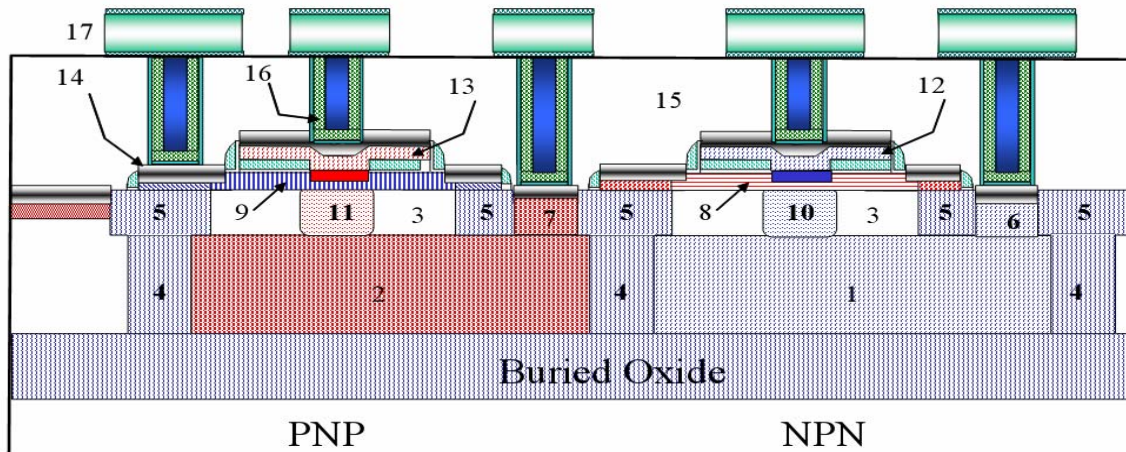
- Collector-Substrate Junction Aids Charge Collection
- SOI Shuts Down Substrate Charge Collection Path



Thick vs Thin Film SOI

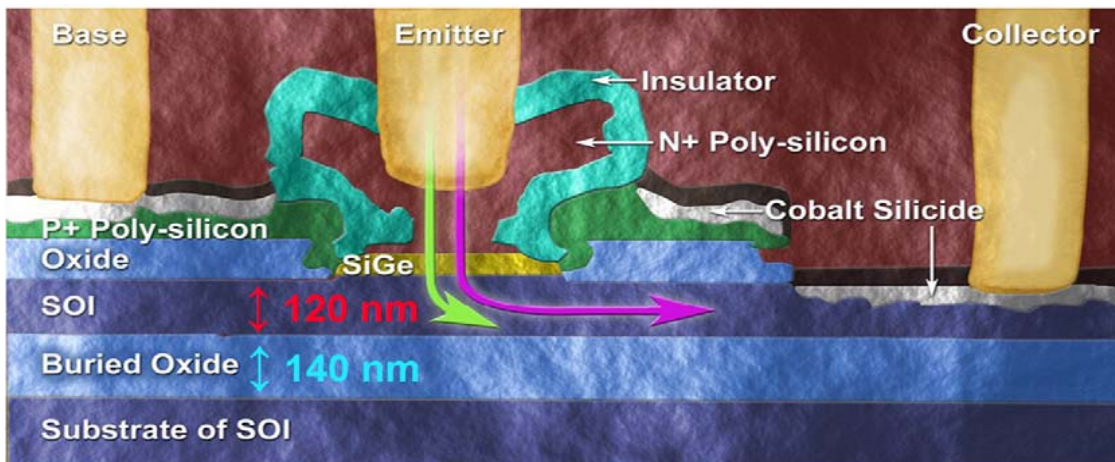


- Thick Film SiGe-on-SOI (TI) - works like a bulk SiGe HBT
- Thin Film SiGe-on-SOI (IBM) - VERY different device!



Thick-Film SOI

↑↓ 1.5 μm SOI



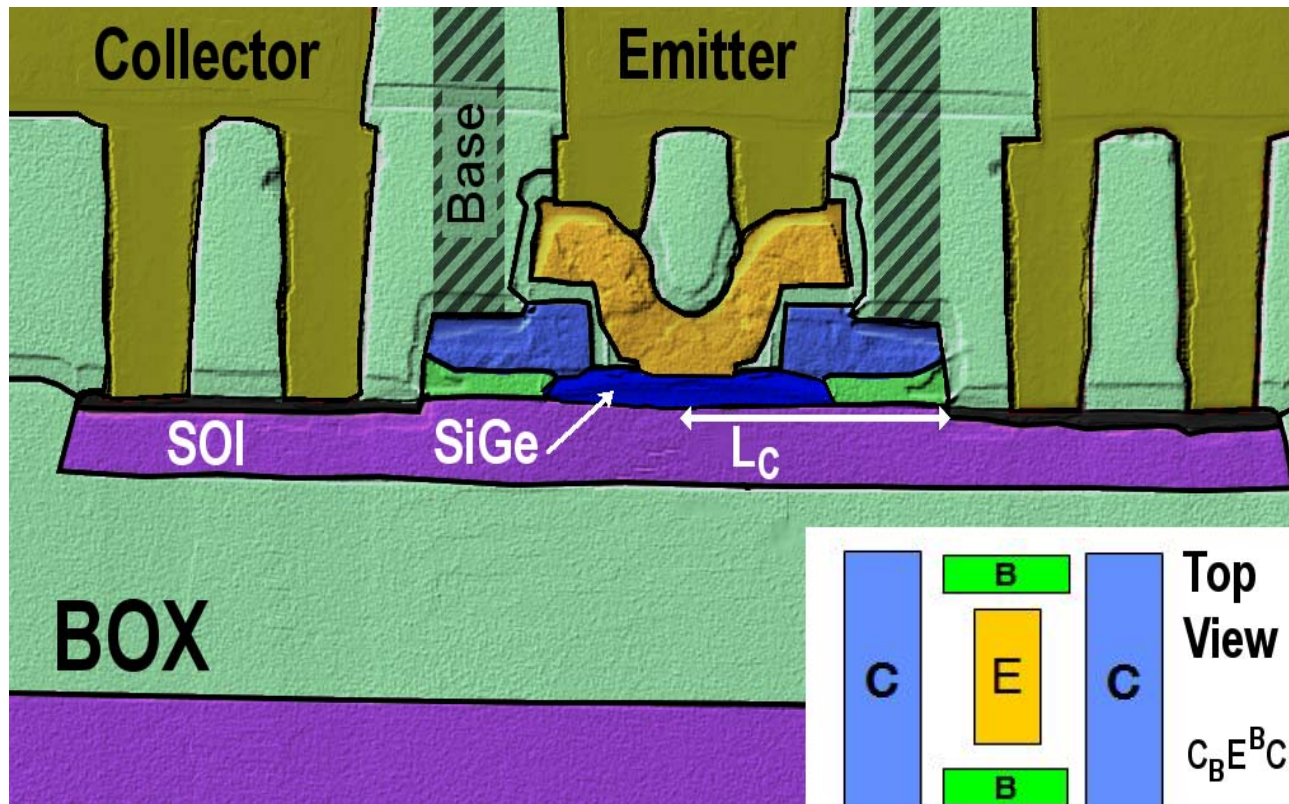
Thin-Film SOI

↑↓ 0.12 μm SOI

New SiGe/SOI Platform



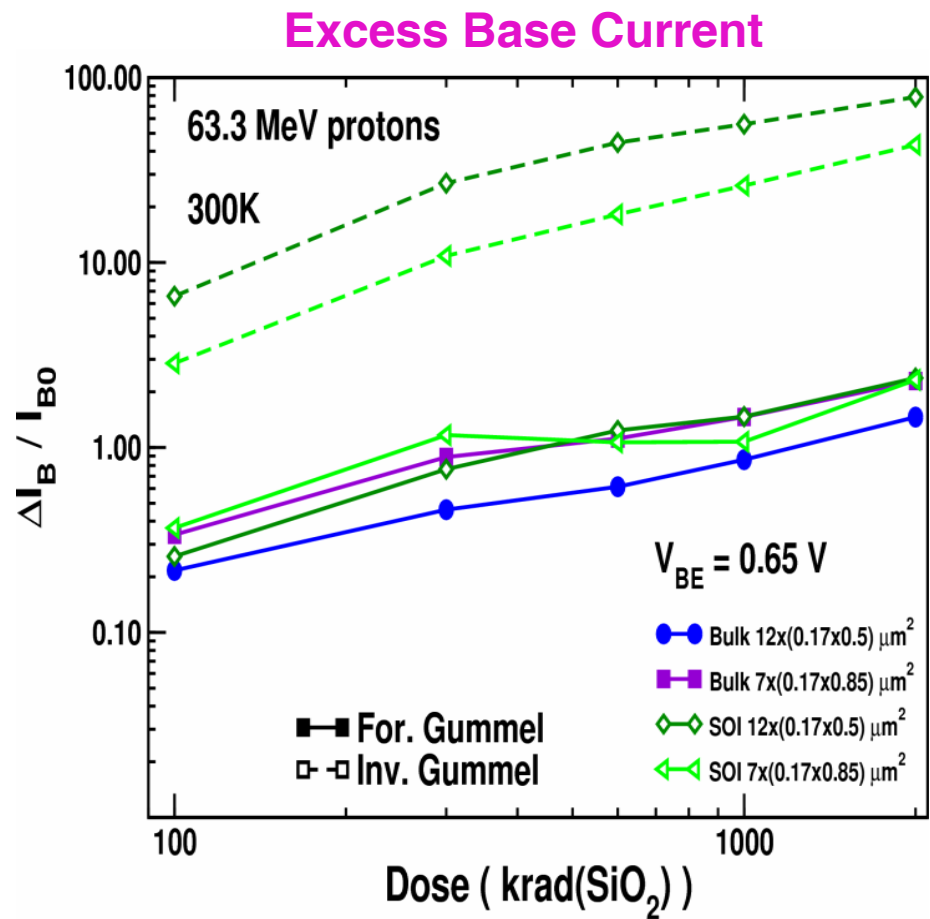
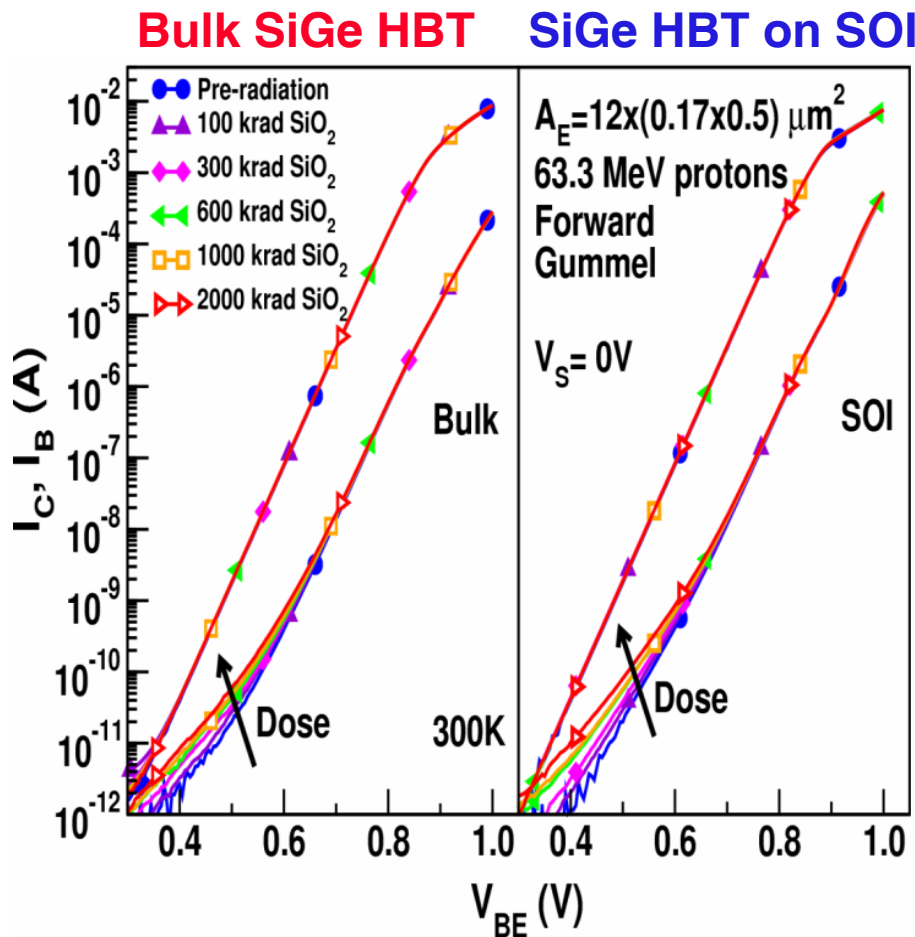
- **ST Microelectronics: SiGe HBT on Thin Film SOI**
 - compatible with 130 nm CMOS/SOI platform (**and C-SiGe!**)
 - uses a folded collector design (novel layout)
 - **npn SiGe HBT:** peak f_T / BV_{CE0} of 70 GHz / 2.3 V (34 / 5.5)
 - **pnp SiGe HBT:** peak f_T / BV_{CE0} of 39 GHz / 2.9 V (17 / 6.7)



Proton DC Response



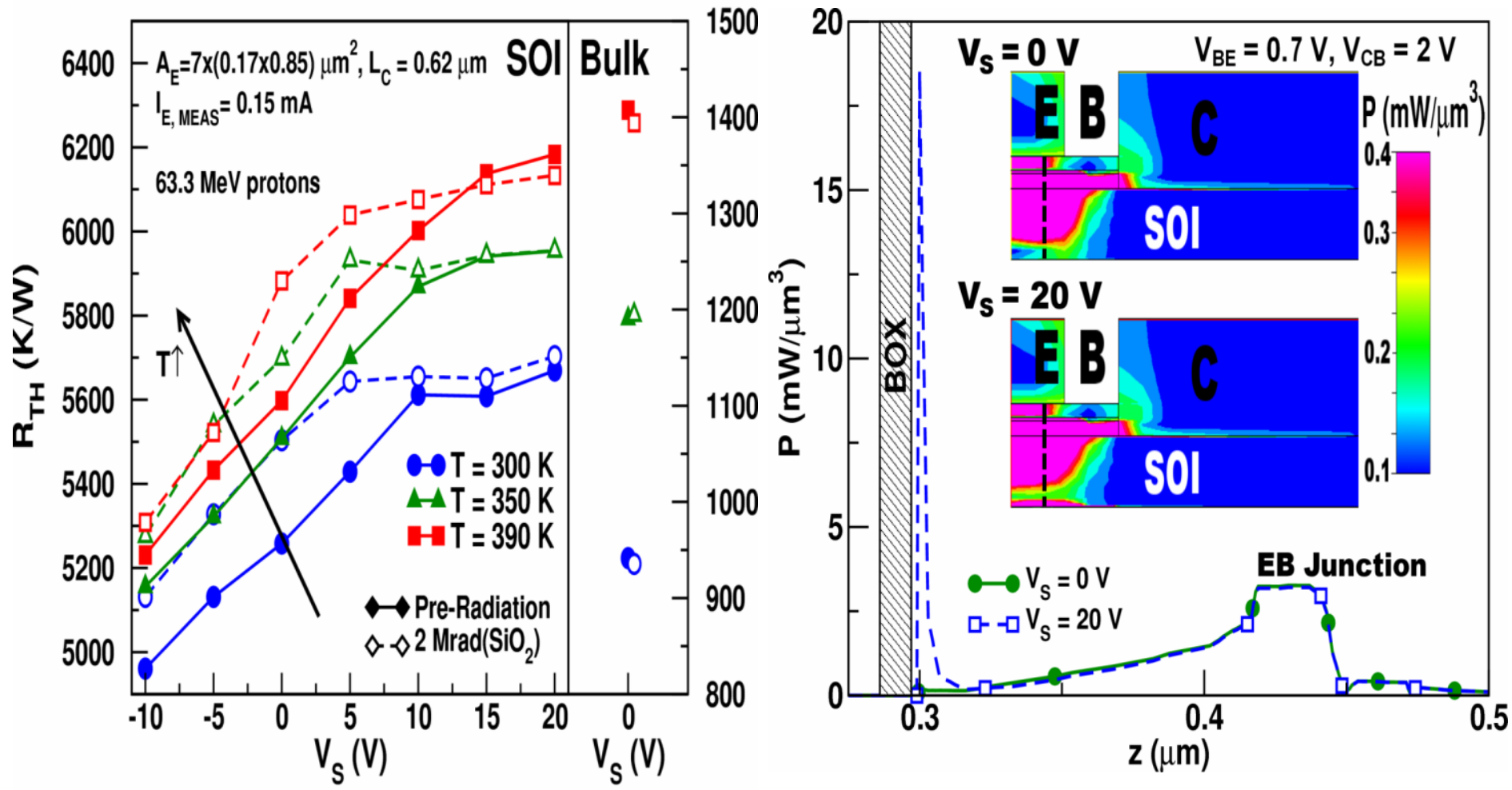
- SOI and Bulk Devices with Identical EB Structure
- No Degradation Introduced by SOI





Thermal Resistance

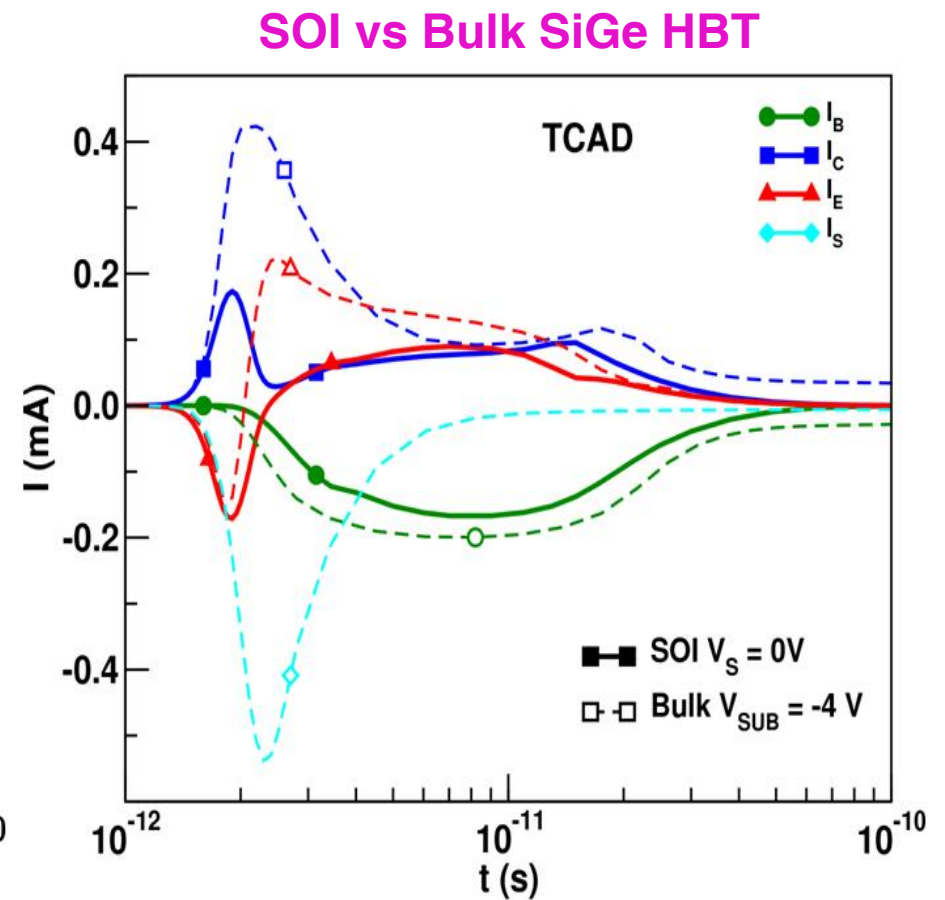
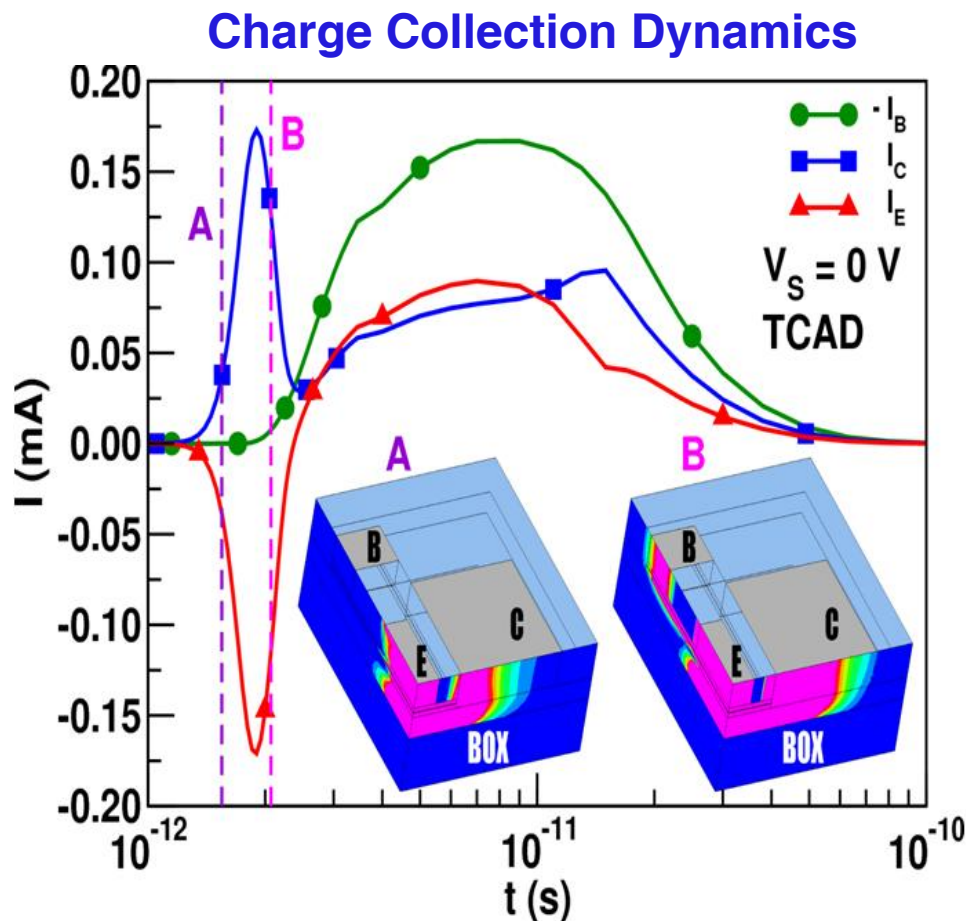
- R_{TH} of HBT-on-SOI Increases with V_S and Radiation
- More Power Dissipated at the SOI / BOX Interface



SEU TCAD in SiGe/SOI



- Unusual Charge Collection Dynamics (true 3-D effects)
- Strong SEU Advantage for SOI Compare to Bulk



Outline

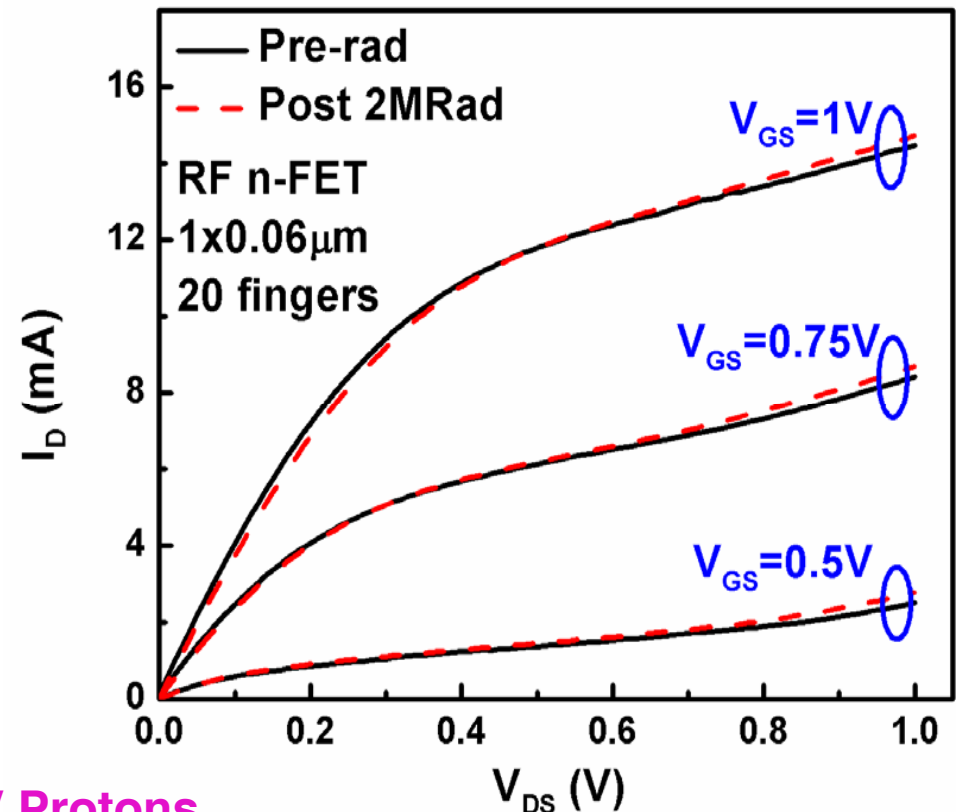
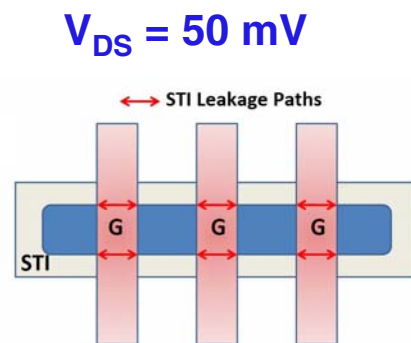


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65nm SOI RF-CMOS (DC)



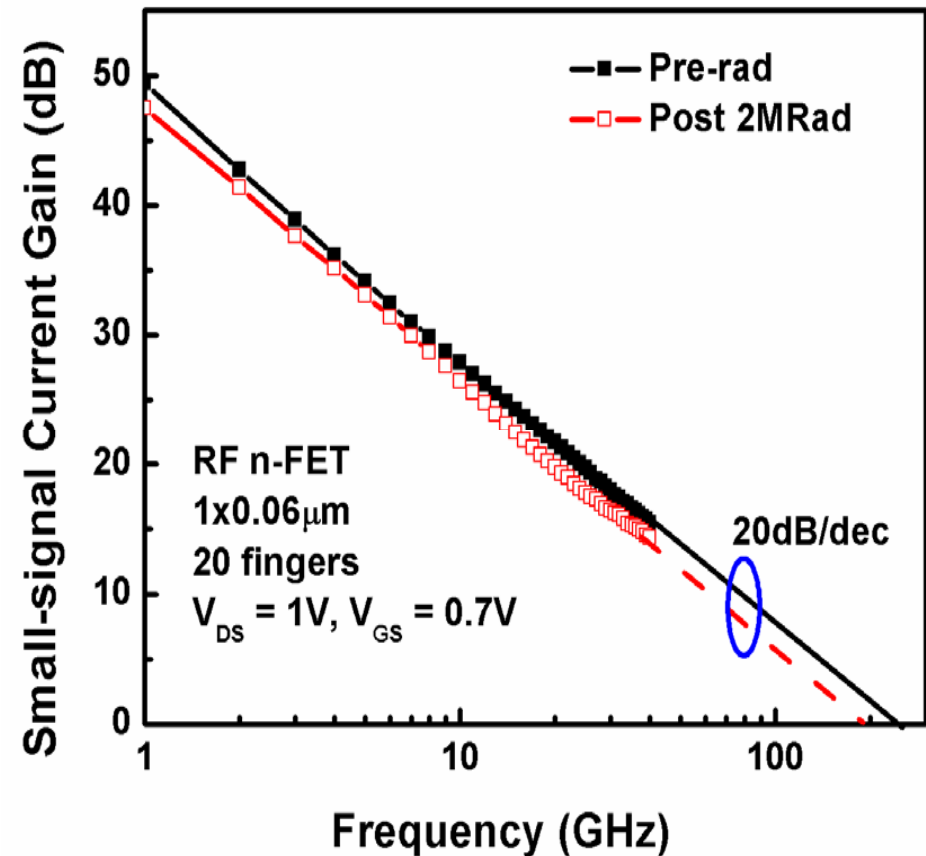
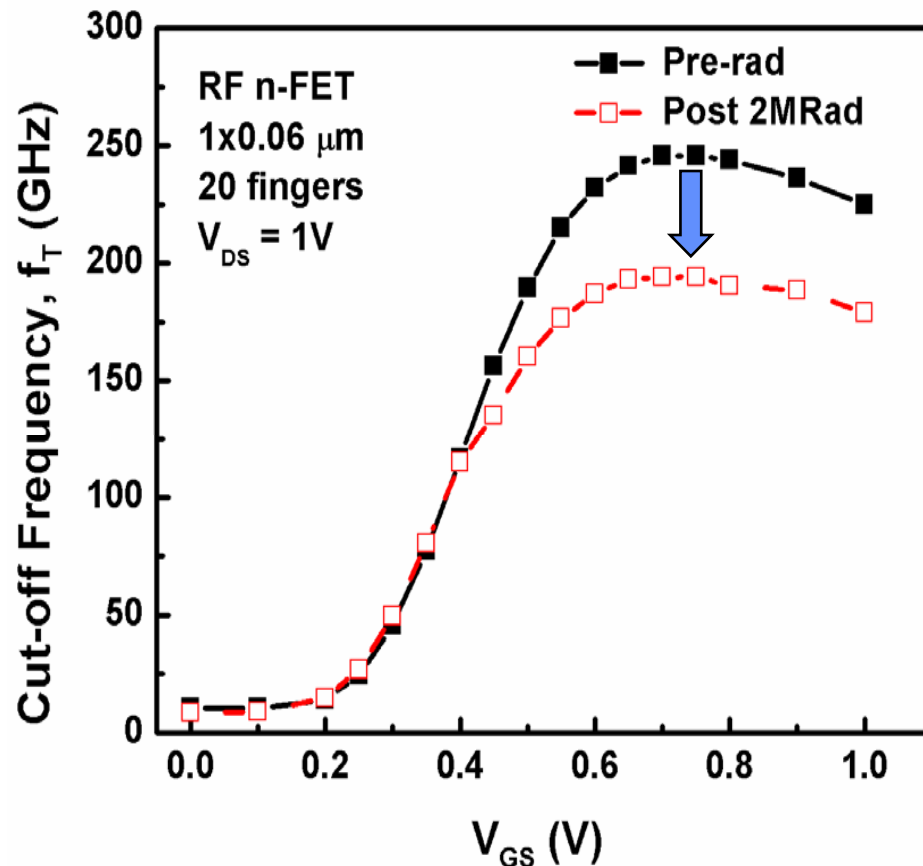
- 65 nm RF-CMOS on SOI (IBM) – **Uses Strain Engineering**
- High f_T / f_{max} in CMOS Comes Only at VERY High W (# fingers)
- Impact of Radiation-Induced Damage on DC Characteristics
 - sub-threshold degradation + enhanced floating body effects



63 MeV Protons



- **Radiation Impact on RF Characteristics of 65 nm RFCMOS/SOI**
 - 63 MeV Proton irradiation degrades f_T considerably
 - h_{21} degradation observed at 2 Mrad total dose

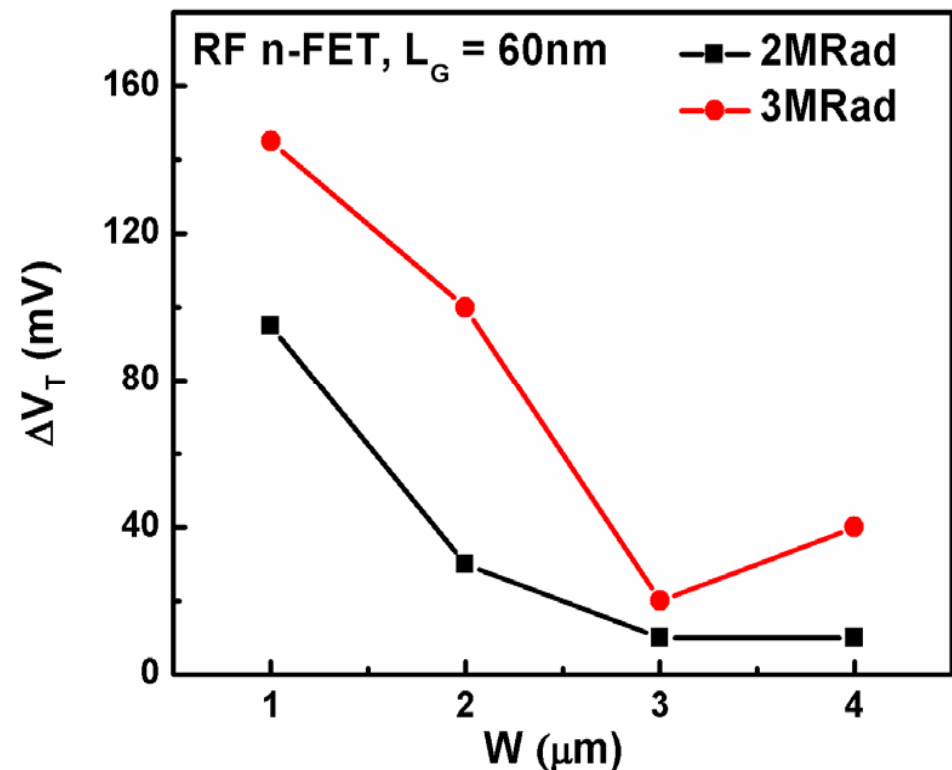
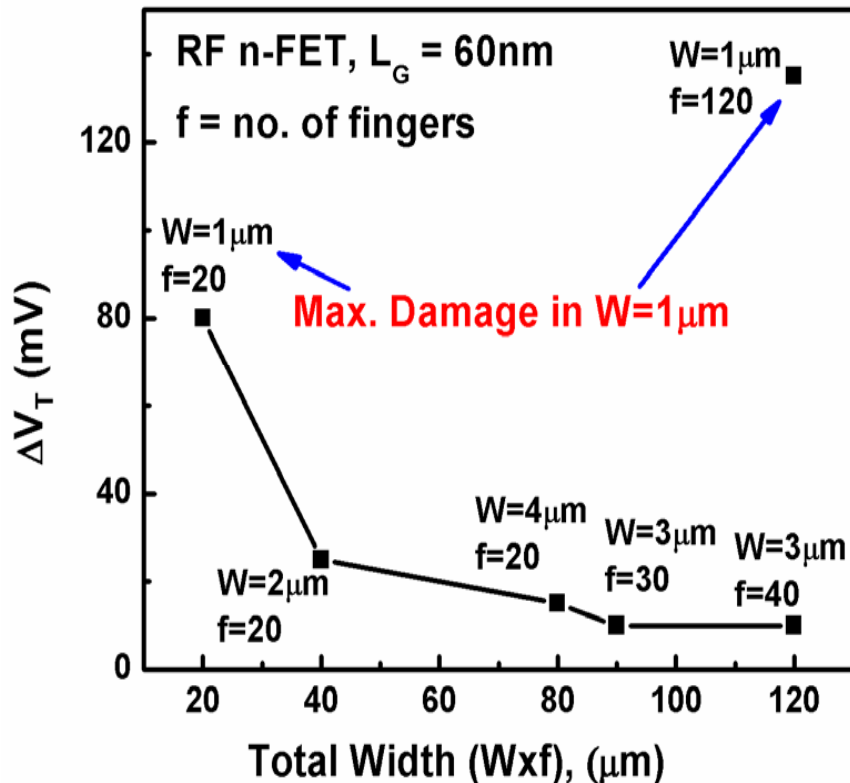




Geometrical Issues

- **Impact of Radiation-Induced Damage on DC Characteristics**
 - damage is highly W dependent
 - suggestive of STI sidewall parasitic conduction (not BOX)
 - **response of logic nFET very different than RF nFET**

Post 2MRad





- **SiGe Offers Great Potential for Many DoD Applications**
 - SiGe HBT + Si CMOS (RF to mm-wave + analog + digital for SoC / SoP)
- **Many Issues in SiGe Still Need Attention**
 - improved understanding of basic damage mechanisms (TID + SEE)
 - understand the effects of temperature on damage mechanisms / SEE
 - need to assess SET in analog/mixed-signal SiGe circuits (**in progress**)
 - explore other SiGe HBT variants (SiGe HBT on SOI, C-SiGe, etc.)
 - explore other (new) SiGe-based devices (SiGe n/p-MODFETs, RF-CMOS)
 - develop new RHBD approaches (device + circuit) for SEE mitigation
 - need improved 3D TCAD for understanding SEE (and TID)
- **Lots of Leverage for SiGe Hardware / Testing Activity**
 - **many** SiGe tapeouts (IBM, IHP, TI, Jazz, ST): **devices + circuits**
 - DTRA / NASA-NEPP (Paul Marshall)
 - NASA SiGe ETDP Project (RHESE)
 - CFDRC SBIR (DTRA / NASA) for Improved TCAD for SEU / Cryo-T, etc.
 - excellent collaboration between Georgia Tech and Vanderbilt teams



2008 Papers

- [1] M. Bellini, S.D. Phillips, R.M. Diestelhorst, P. Cheng, J.D. Cressler, P.W. Marshall, M. Turowski, G. Avenier, A. Chantre, and P. Chevalier, "Novel Total Dose and Heavy-Ion Charge Collection Phenomena in a New SiGe HBT on Thin-Film SOI Technology," *IEEE Nuclear and Space Radiation Effects Conference*, paper E-4, 2008.
- [2] T.K. Thrivikraman, P. Cheng, S.D. Phillips, J.P. Comeau, M.A. Morton, J.D. Cressler, and P.W. Marshall, "On the Radiation Tolerance of SiGe HBT and CMOS-Based Phase Shifters for Space-Based, Phased Array Antenna Systems," *IEEE Nuclear and Space Radiation Effects Conference*, paper PE-4, 2008.
- [3] L. Najafizadeh, S.D. Phillips, P. Cheng, J.D. Cressler, T. Vo, M. Mojarradi, and P.W. Marshall, "The Effects of Proton Irradiation on the Performance of High-Voltage nMOSFETs implemented in a Low-Voltage SiGe BiCMOS Platform," *IEEE Nuclear and Space Radiation Effects Conference*, paper PE-5, 2008.
- [4] J.A. Pellish, R.A. Reed, N.D. Pate, D. McMorrow, J.S. Melinger, J.A. Kozub, P.W. Marshall, A.K. Sutton, R.M. Diestelhorst, S. Phillips, J.D. Cressler, R.A. Weller, R.D. Schrimpf, and G.F. Niu, "Radiation-Induced Current Transients in SiGe HBTs," *IEEE Nuclear and Space Radiation Effects Conference*, paper PA-8, 2008.
- [5] X. Wei, T. Zhang, G. Niu, M. Varadharajaperumal, J. D. Cressler, and P. W. Marshall, "3-D Mixed Mode Simulation of Single Event Transients in SiGe HBT Emitter Followers and Hardening Guidelines," *IEEE Nuclear and Science Radiation Effects Conference*, paper PF-5, 2008.
- [6] J.D. Cressler, "Silicon-Germanium as an Enabling IC Technology for Extreme Environment Electronics," *Proceedings of the 2008 IEEE Aerospace Conference*, pp. 1-7 (on CD ROM), 2008. **(invited)**



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